

# Screening of excitations and small polarons in strongly correlated solids and solid surfaces



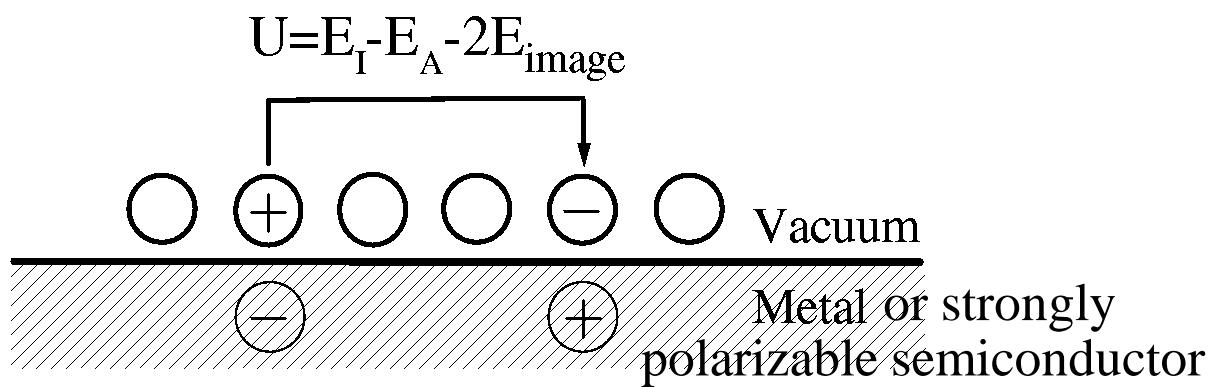
Hao Tjeng

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- Tim Haupricht, Thomas Lorenz – *Univ. Cologne*
- Andreas Reisner, Katharina Höfer, Christoph Becker, Roger Chang, Maurits Haverkort, Zhiwei Hu – *MPI Dresden*
- Yen-Fa Liao, Ku-Ding Tsuei, Hong-Ji Lin, Chien-Te Chen – *NSRRC, Taiwan*

# Modification of material properties using image charge screening



Reduction of charge excitation energies:

- Coulomb energy:  $U = U_o - 2E_{\text{image}}$
- Charge transfer energy:  $\Delta = \Delta_o - 2E_{\text{image}}$
- Bandgap:  $E_g = E_{go} - 2E_{\text{image}}$

Expectations:

- Stronger (super)exchange interactions:  $\sim t^2/U$  or  $\sim t^4/\Delta^2(1/U - 1/\Delta)$
- Higher  $T_C$  and  $T_N$  ?!!

# Strongly reduced band gap in a correlated insulator in close proximity to a metal

*Europhys. Lett.*, **40** (2), pp. 177-182 (1997)

R. HESPER, L. H. TJENG and G. A. SAWATZKY

*Solid State Physics Laboratory, Materials Science Centre, University of Groningen  
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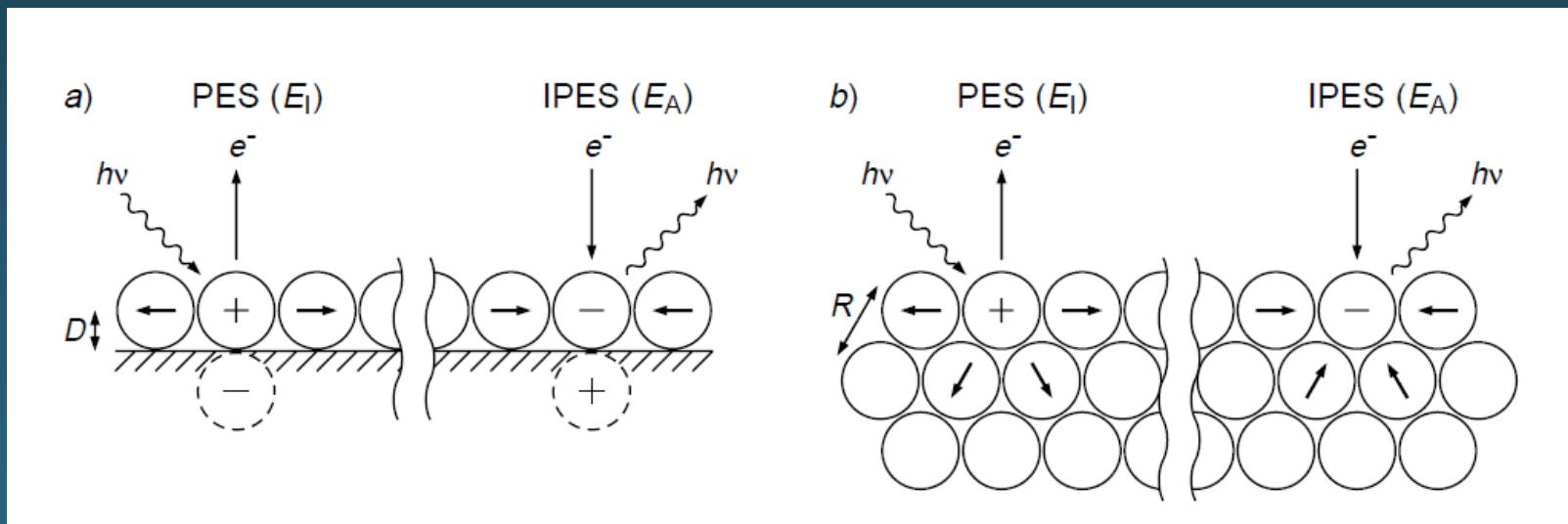
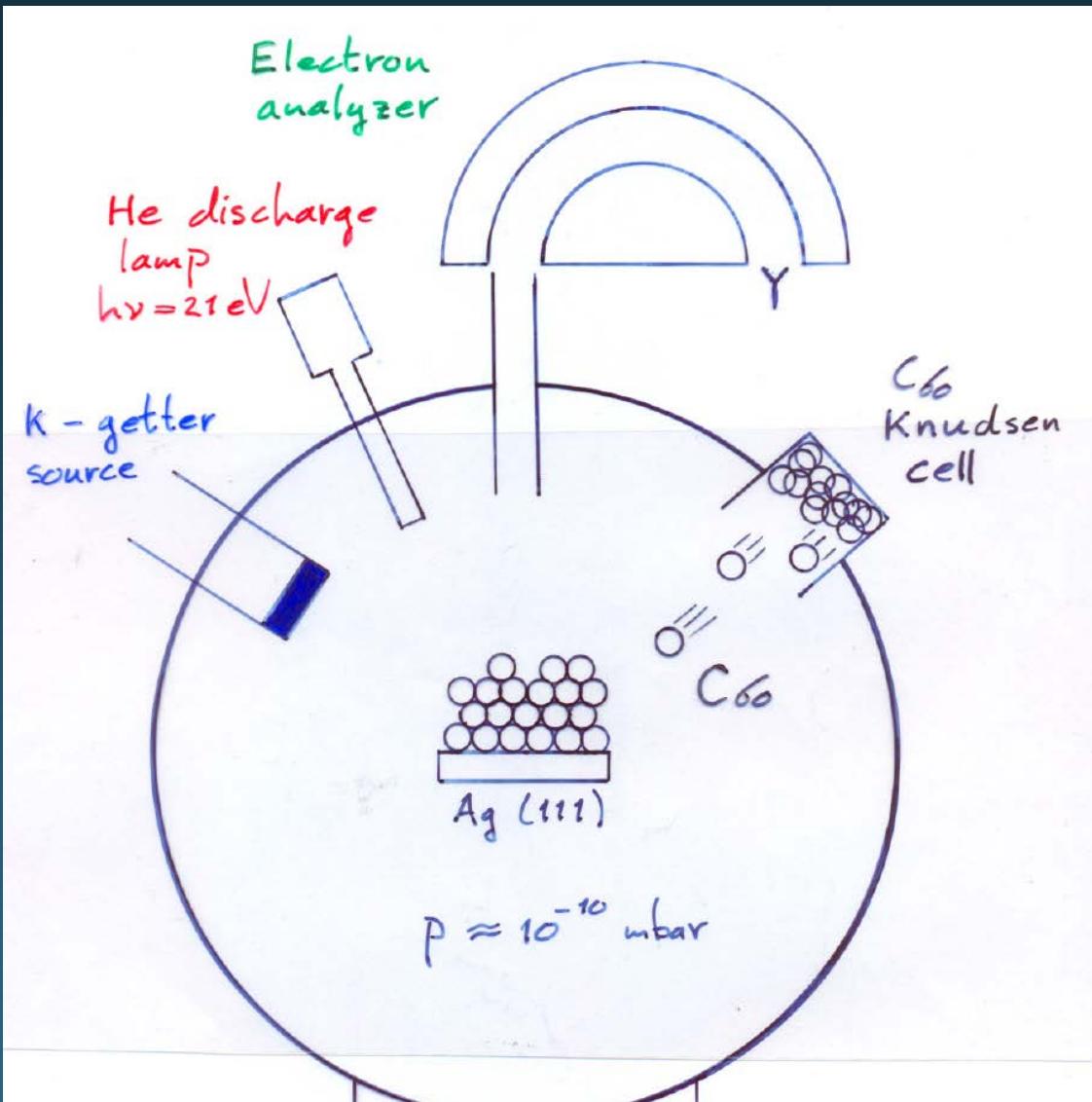
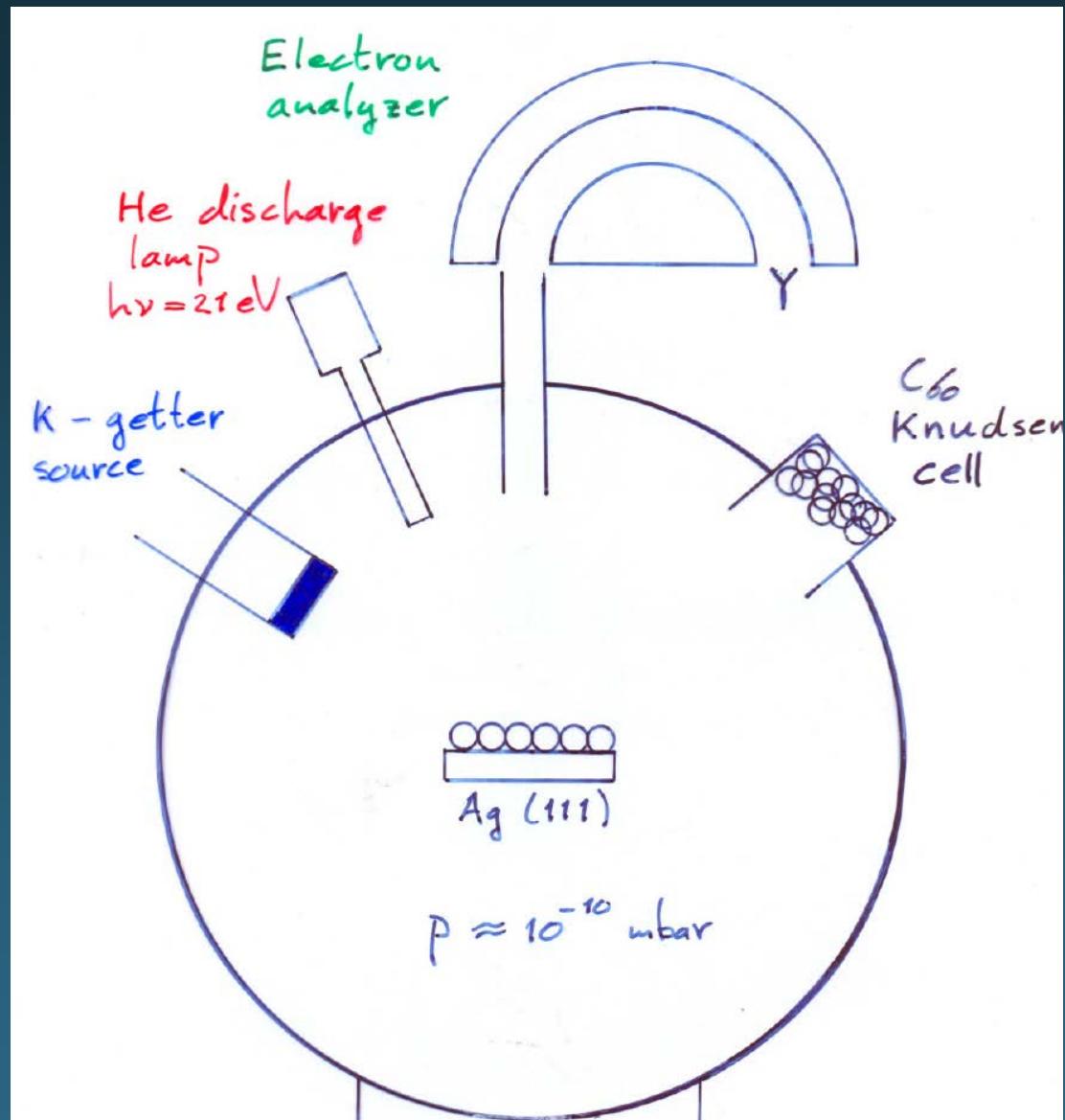
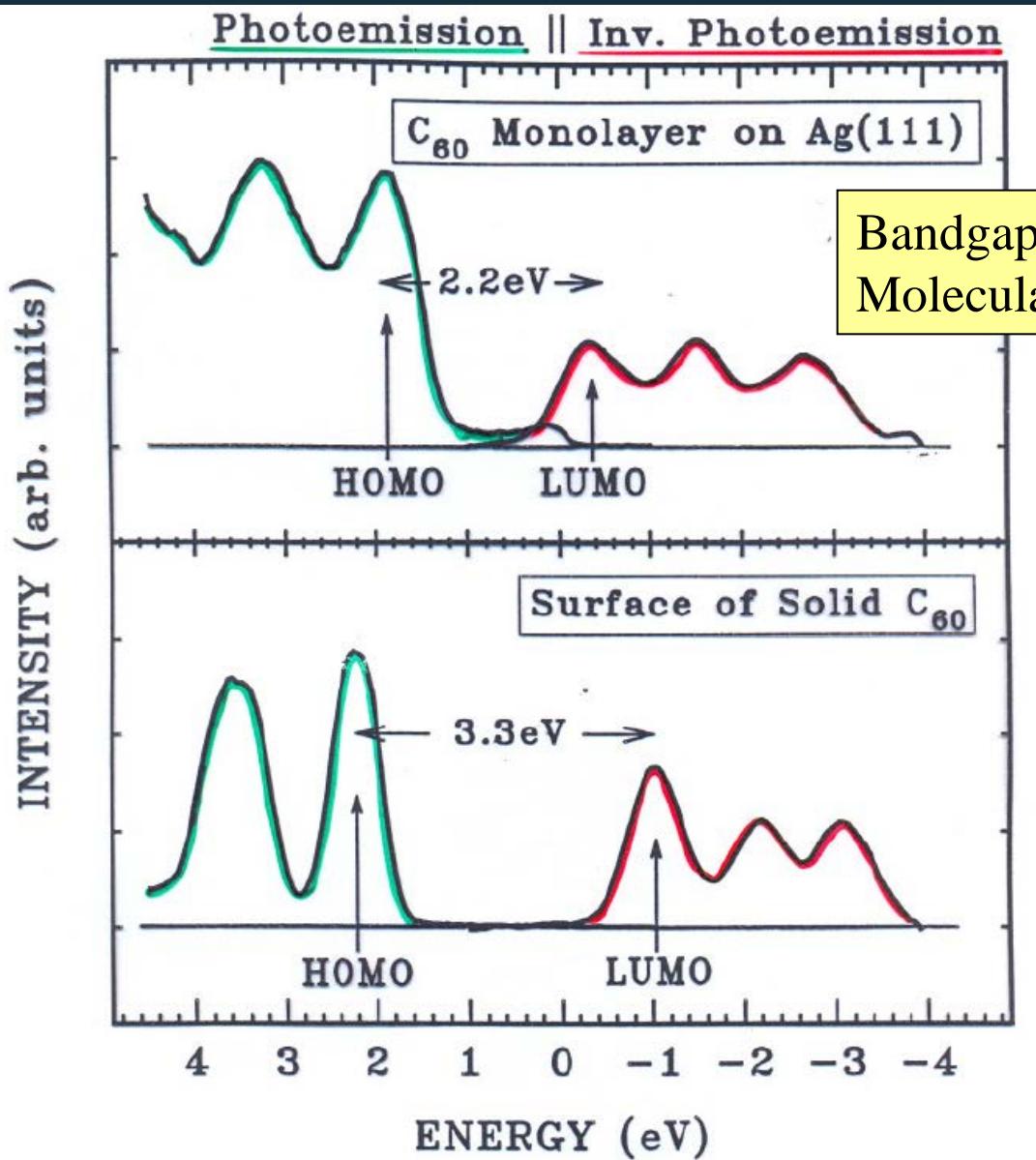


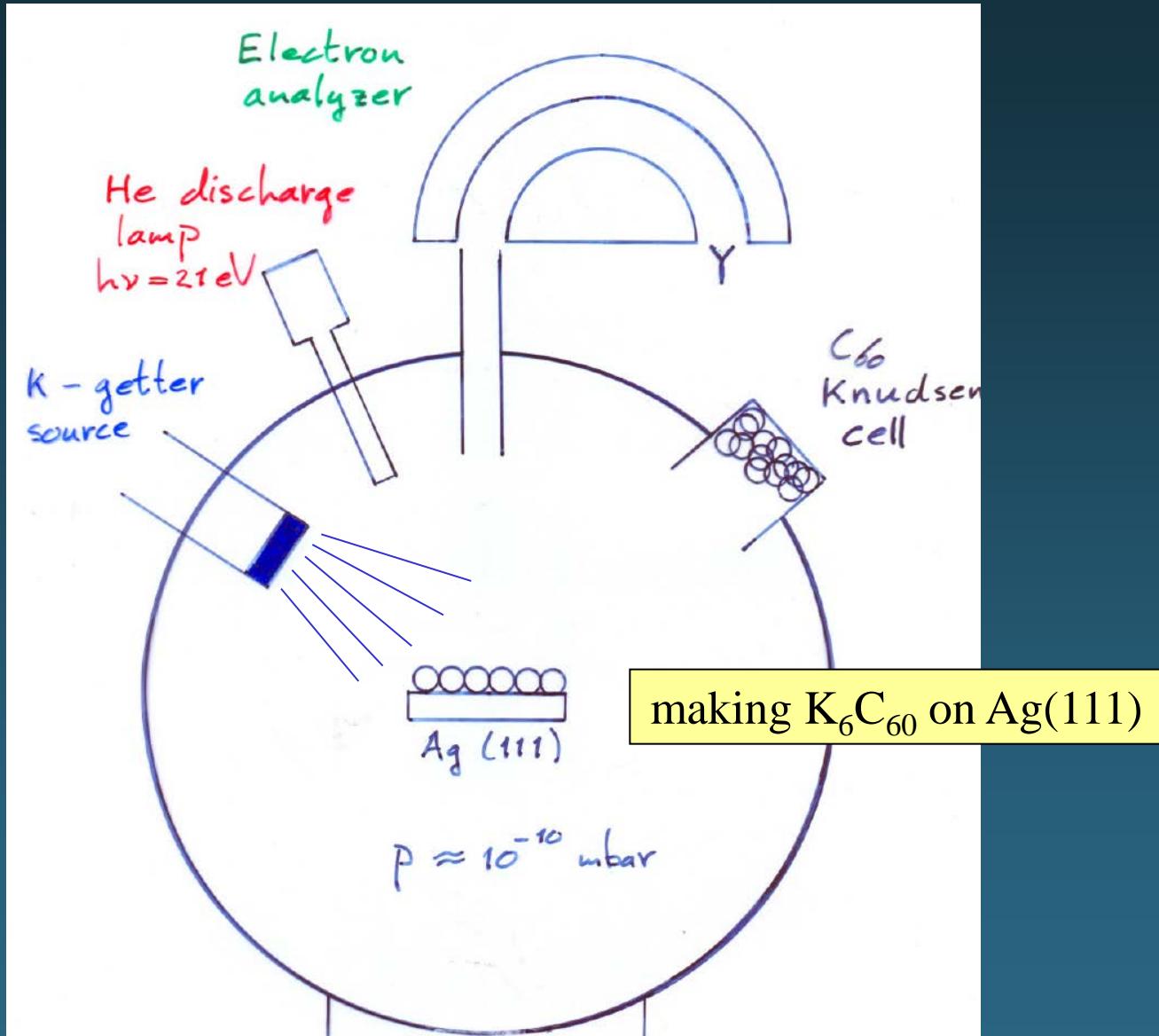
Fig. 3. – Photoemission and inverse photoemission processes for a monolayer of C<sub>60</sub> on metal (a) and for the surface of bulk C<sub>60</sub> (b). In both cases, the final state charges and polarizations of the bucky-balls are indicated.

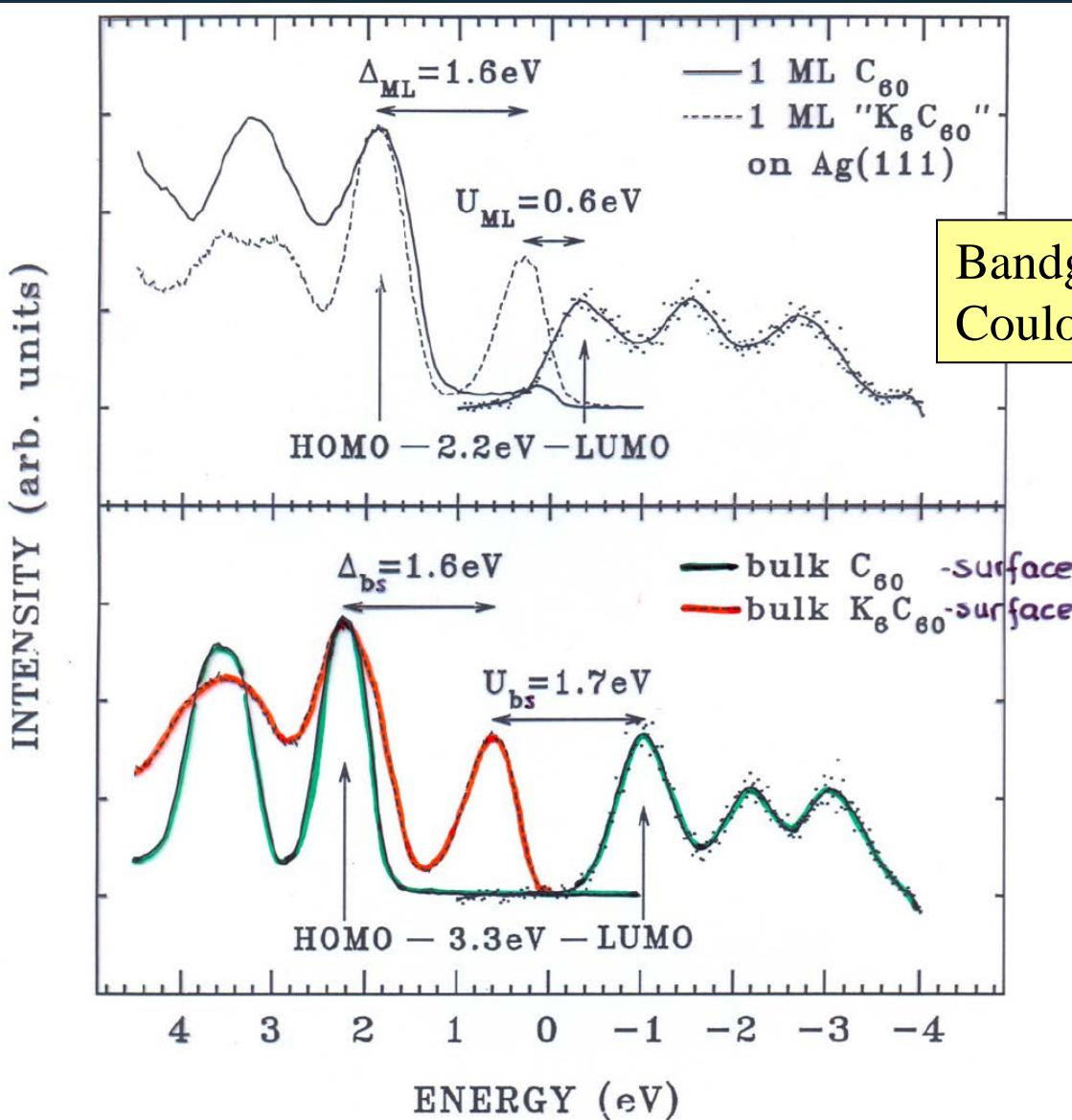




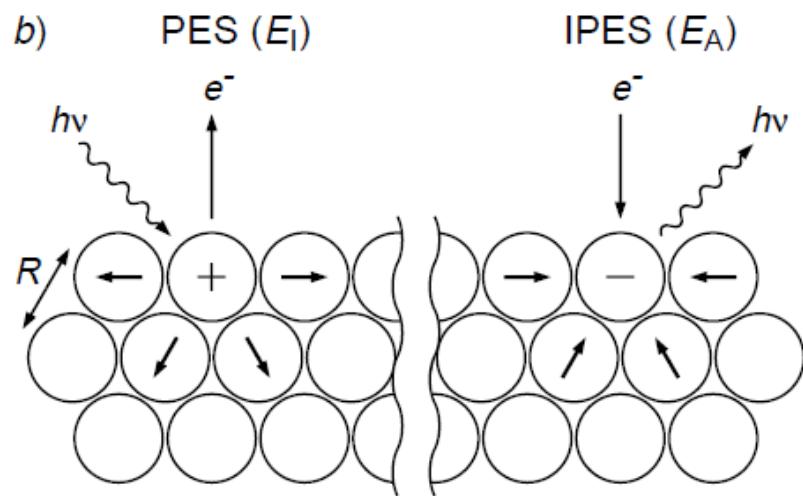
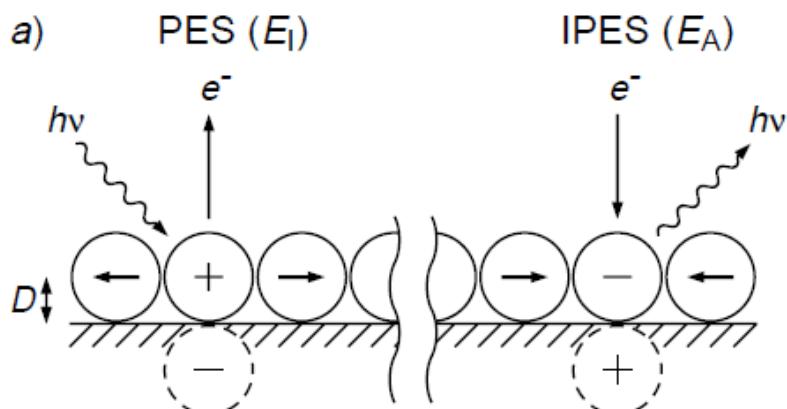


Bandgap is reduced! Rigidly!  
Molecular orbital structure is conserved!





Bandgap is reduced because on-site Coulomb energy  $U$  is reduced!



$$E_g = E_g^{at} - 2E_p(C_{60}) - 2E_p(\text{metal})$$

$$\downarrow \quad \downarrow \quad \downarrow \quad \vdots$$

$$2.2 \text{ eV} \quad 5.0 \text{ eV} \quad 1.2 \text{ eV} \rightarrow 1.6 \text{ eV}$$

(6 nearest neighbors)

$$E_g = E_g^{at} - 2E_p(C_{60})$$

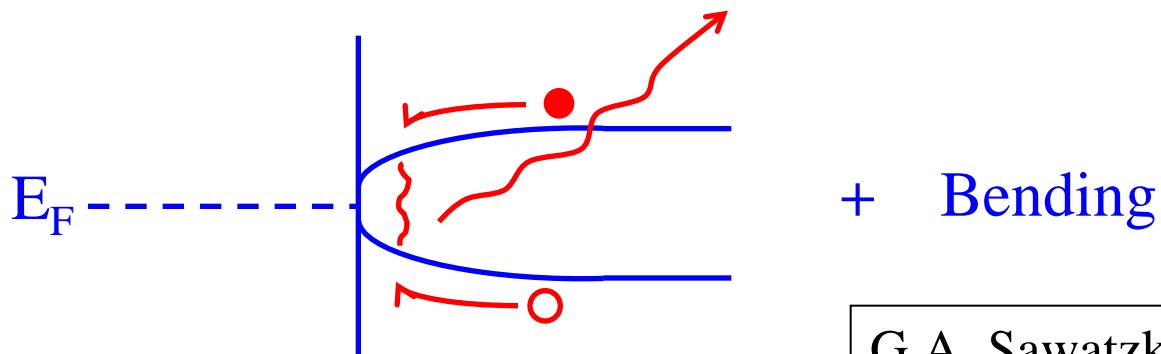
$$\downarrow \quad \downarrow \quad \vdots$$

$$3.3 \text{ eV} \quad 5.0 \text{ eV} \rightarrow 1.7 \text{ eV}$$

(9 nearest neighbors)

$$2E_p(\text{metal} = \text{image charge}) = \frac{e^2}{2D} = 1.44 \text{ eV} \quad (D \approx 5 \text{ \AA})$$

## bandgap of semiconductor near interface



G.A. Sawatzky

STM/STS: influence of the tip on the observed bandgap of semiconductors ?!

# **Electronic Structure of Oxide Thin Films on Metals**



**Salvatore Altieri**

Phys. Rev. B 66  
155432 (2002)

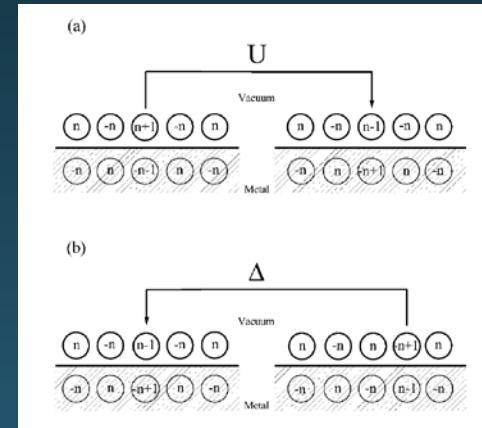
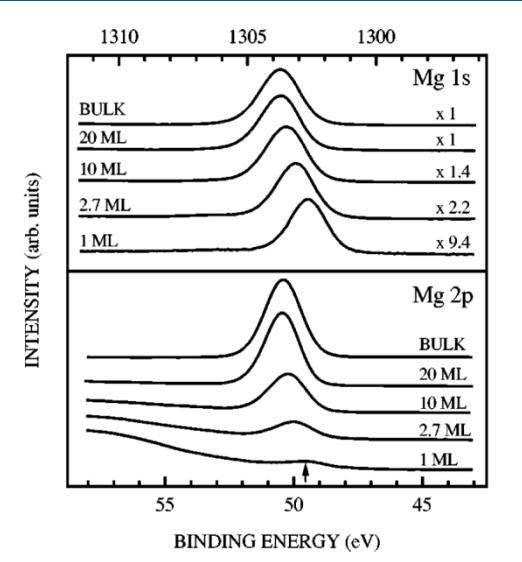
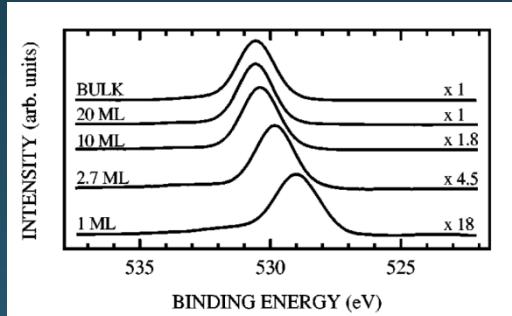
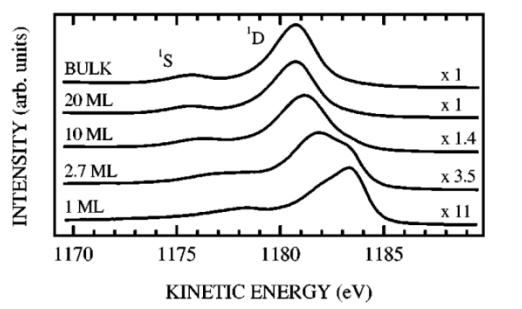
## Reduction of Coulomb and charge-transfer energies in oxide films on metals

S. Altieri and L. H. Tjeng F. C. Voogt and T. Hibma G. A. Sawatzky

Thin Solid Films  
400 (2001) 9-15

$$E_{kin}^{KLL} = E_b^{1s} - 2E_b^{2p} - U,$$

$$\delta\Delta = \delta E_b^{1s}(O) - \delta E_b^{1s}(Mg) + \delta U(Mg)$$



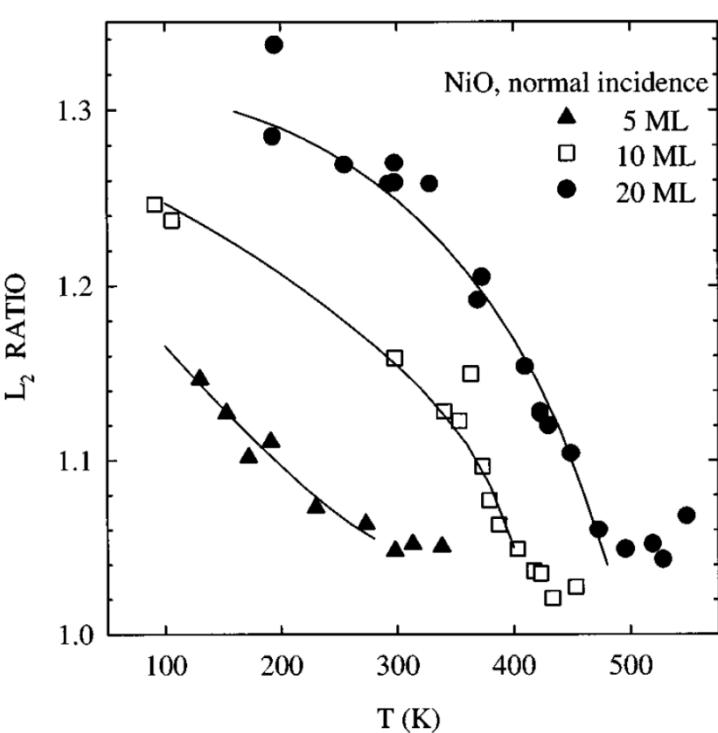
	1 ML	2.7 ML	10 ML	20 ML	Bulk
$U(\text{Mg } 2p(^1D))$	20.3	21.3	21.7	22.1	22.1
$\delta U(\text{Mg } 2p)$	-1.8	-0.8	-0.4	0	0
$\delta\Delta(\text{O } 2p \rightarrow \text{Mg } 3s)$	-2.5	-1.2	-0.5	0	0

# Image charge screening: A new approach to enhance magnetic ordering temperatures in ultrathin correlated oxide films

S. Altieri,<sup>1</sup> M. Finazzi,<sup>2</sup> H. H. Hsieh,<sup>3</sup> M. W. Haverkort,<sup>4</sup> H.-J. Lin,<sup>5</sup> C. T. Chen,<sup>5</sup> S. Frabboni,<sup>1,6</sup> G. C. Gazzadi,<sup>1</sup> A. Rota,<sup>6</sup> S. Valeri,<sup>1,6</sup> and L. H. Tjeng<sup>4</sup>

## Thickness dependence of magnetic ordering temperature of oxide thin films

NiO on MgO(001)



20 ML:  $T_N = 500$  K  
 10 ML:  $T_N = 400$  K  
 5 ML:  $T_N = 250$  K

# Image charge screening: A new approach to enhance magnetic ordering temperatures in ultrathin correlated oxide films

S. Altieri,<sup>1</sup> M. Finazzi,<sup>2</sup> H. H. Hsieh,<sup>3</sup> M. W. Haverkort,<sup>4</sup> H.-J. Lin,<sup>5</sup> C. T. Chen,<sup>5</sup> S. Frabboni,<sup>1,6</sup> G. C. Gazzadi,<sup>1</sup> A. Rota,<sup>6</sup> S. Valeri,<sup>1,6</sup> and L. H. Tjeng<sup>4</sup>

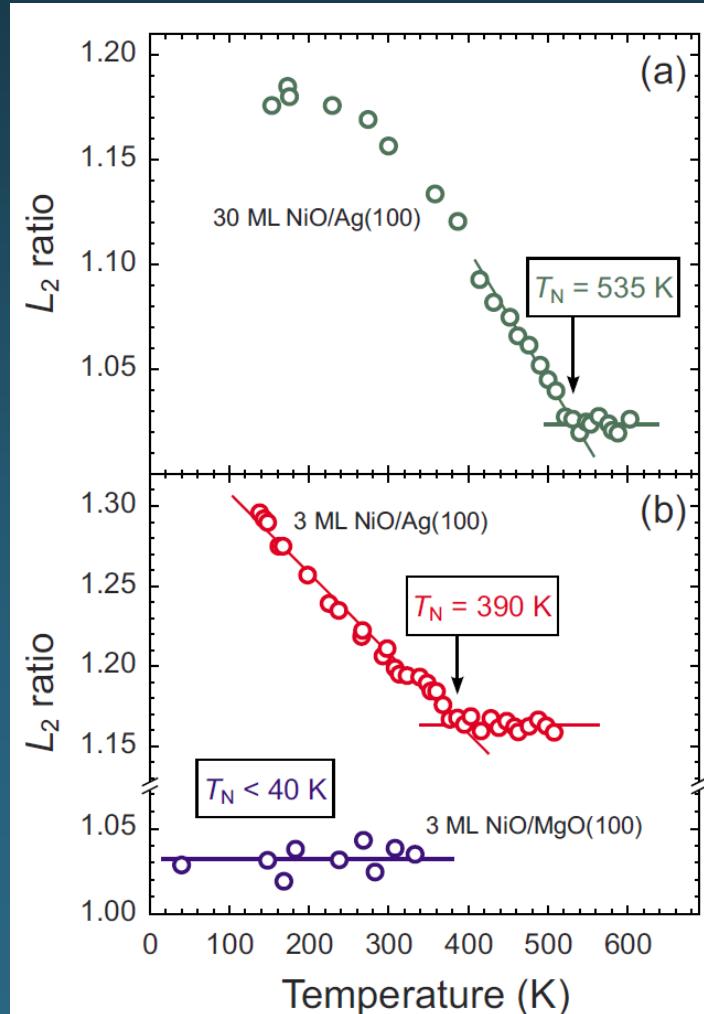
## Thickness dependence of magnetic ordering temperature of oxide thin films

how about NiO on Ag(001) ?

$$J = -\frac{2t^4}{\Delta^2} \left( \frac{1}{\Delta} + \frac{1}{U} \right),$$

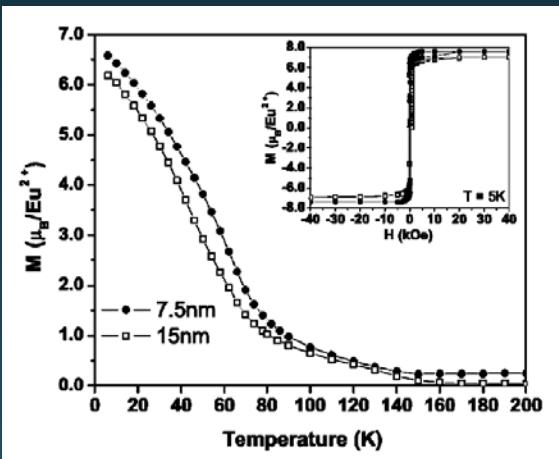
- Coulomb energy:  $U = U_o - 2E_{\text{image}}$
- Charge transfer energy:  $\Delta = \Delta_o - 2E_{\text{image}}$

NiO on Ag(001) 3 ML:  $T_N = 390$  K  
 NiO on MgO(001) 3 ML:  $T_N < 40$  K



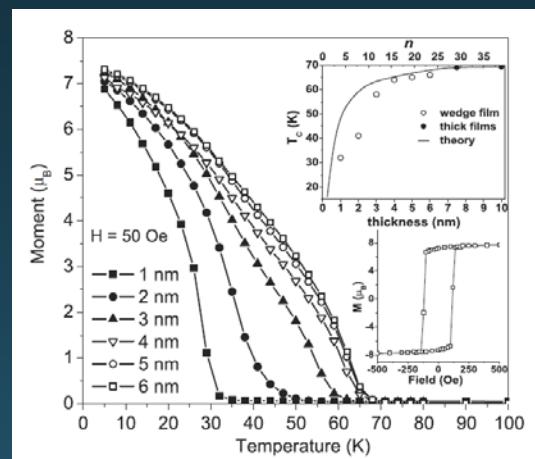
# EuO thin films: thickness dependence of Curie temperature

Si – EuO – Al<sub>2</sub>O<sub>3</sub>



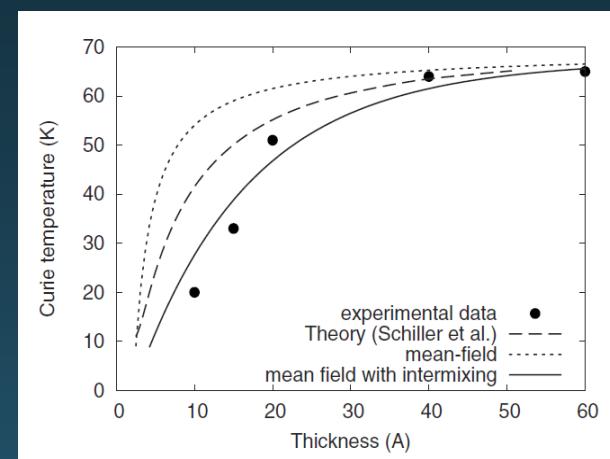
Santos/Moodera PRB 2004

Cr/Cu – EuO – Y/Al



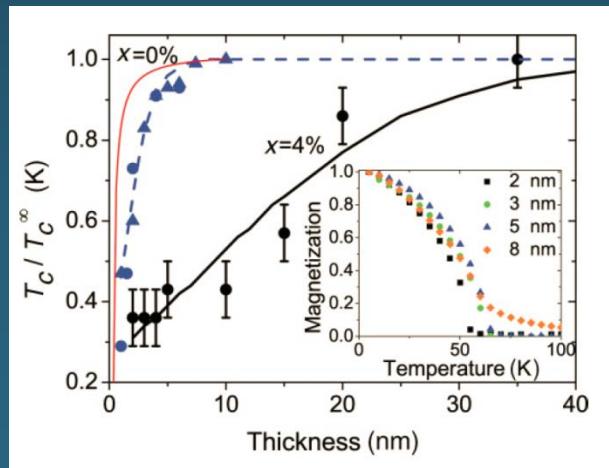
Santos et al. PRL 2008

Al – EuO – Y/Al



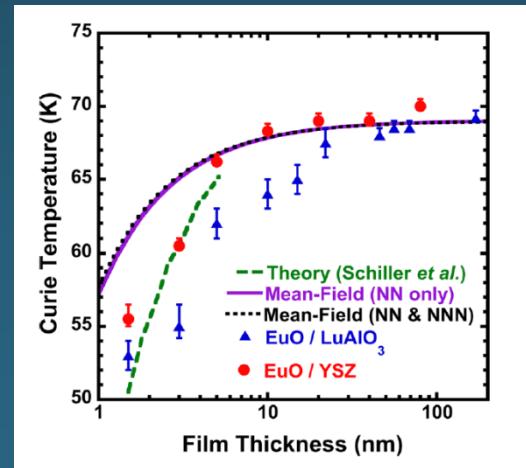
Müller et al. JAP 2009

Pt – EuO - Pt



Barbagallo et al. PRB 2011

YSZ/LuAO– EuO – Si/Al



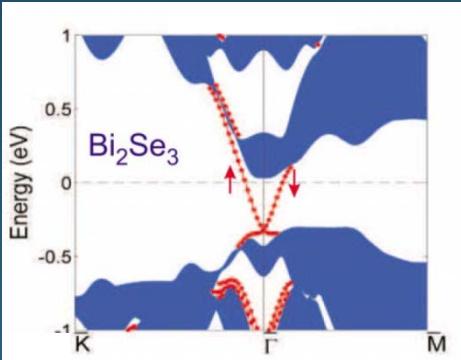
Melville et al. APL 2013

influence of polarizability of buffer/capping layer ??

# Intrinsic conduction through topological surface states of insulating $\text{Bi}_2\text{Te}_3$

*the ultimate surface science challenge ?!*

control of doping at surface



surface impurity concentration  
must be much less than 1%.

minimize doping in bulk

FS volume:  
 $0.1 \times 0.1 \text{ BZ} =$   
 $0.01 \text{ e/u.c.} =$   
few  $10^{12} \text{ e/cm}^2$

10  $\mu\text{m}$  thick sample =  $10^4$  layers  
bulk impurity concentration  
must be much less than 1 ppm

100 nm thin sample =  $10^2$  layers  
bulk impurity concentration  
must be much less than 100 ppm

topological surface states are protected against (non-magnetic) impurity scattering  
but surface is not protected against impurity doping (surface band bending)

## All *in-situ* ultra-high vacuum experiments

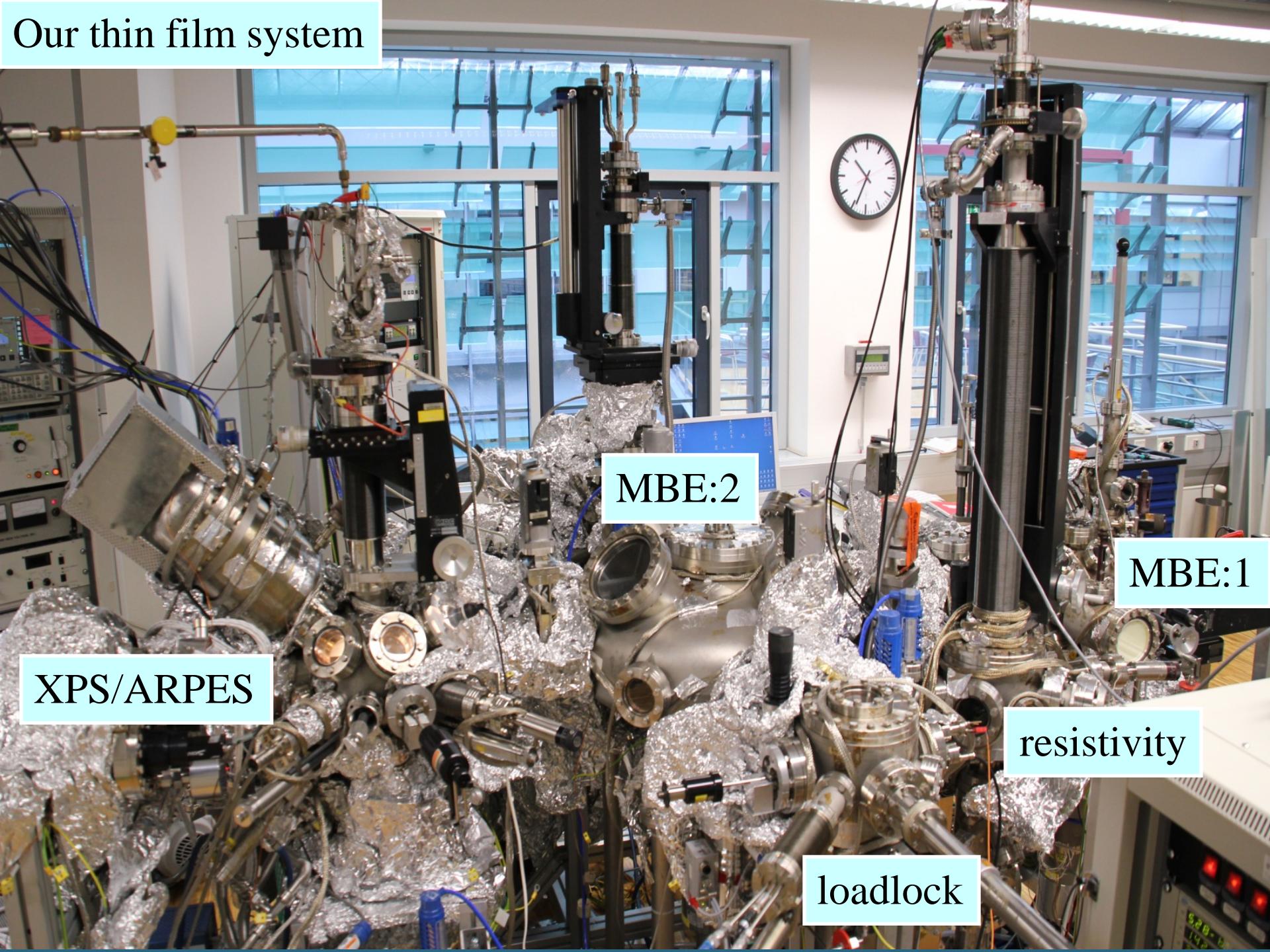
- preparation by true-MBE ( $10^{-10}$  mbar vacuum)
- *in-situ* structure characterization (RHEED, LEED)
- *in-situ* spectroscopy (XPS, ARPES)
- *in-situ* resistivity (four-point probe)

Katharina Höfer, Christoph Becker, Jesse Swanson, Diana Rata

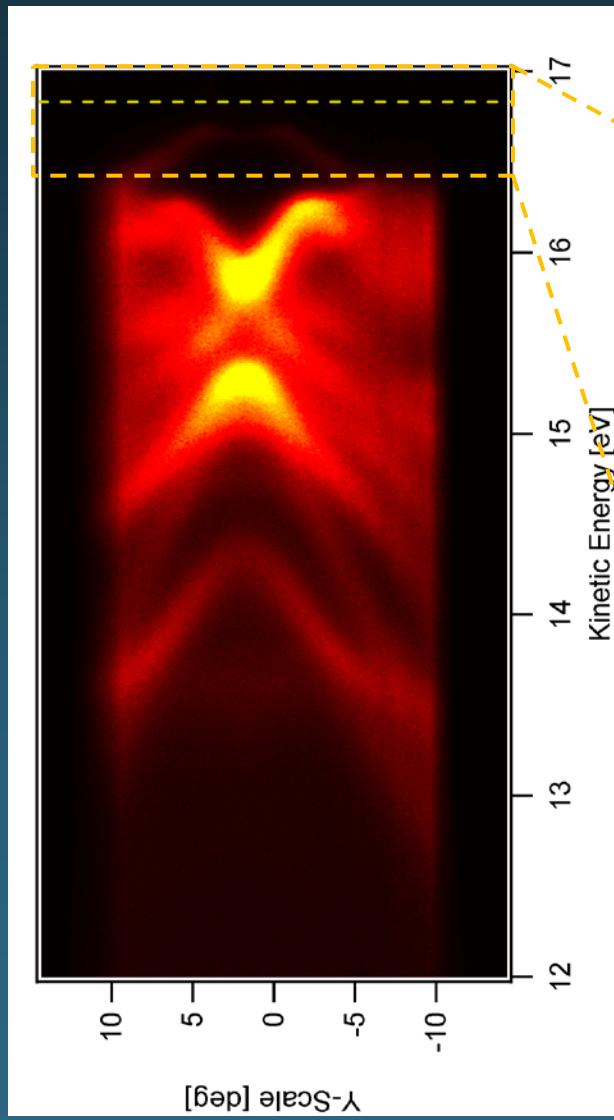


PhD thesis work

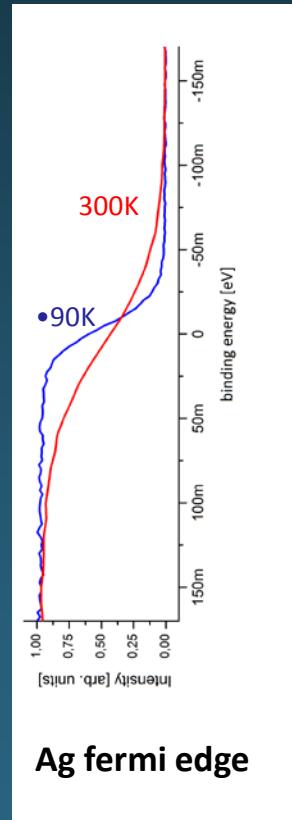
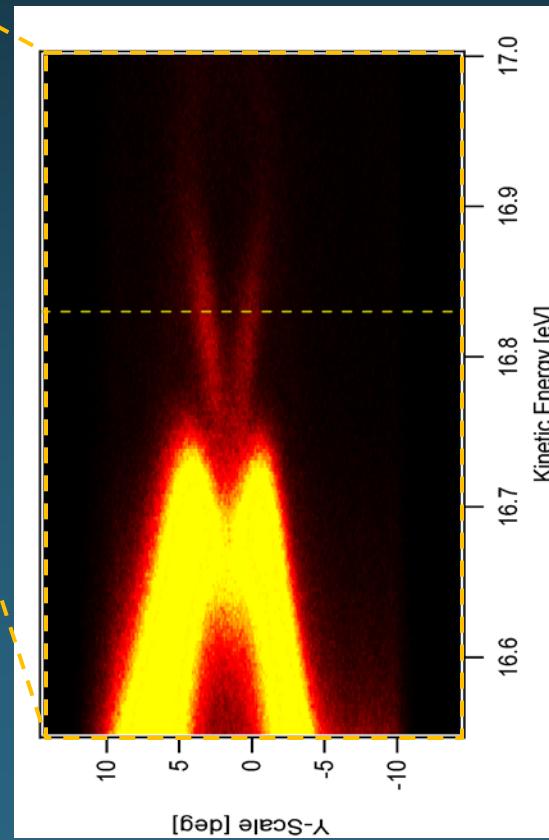
# Our thin film system



# ARPES – surface/bulk



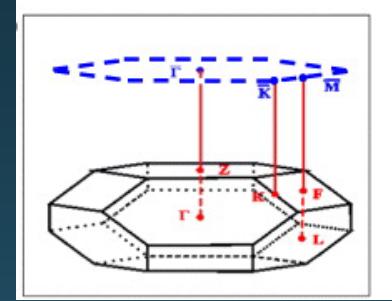
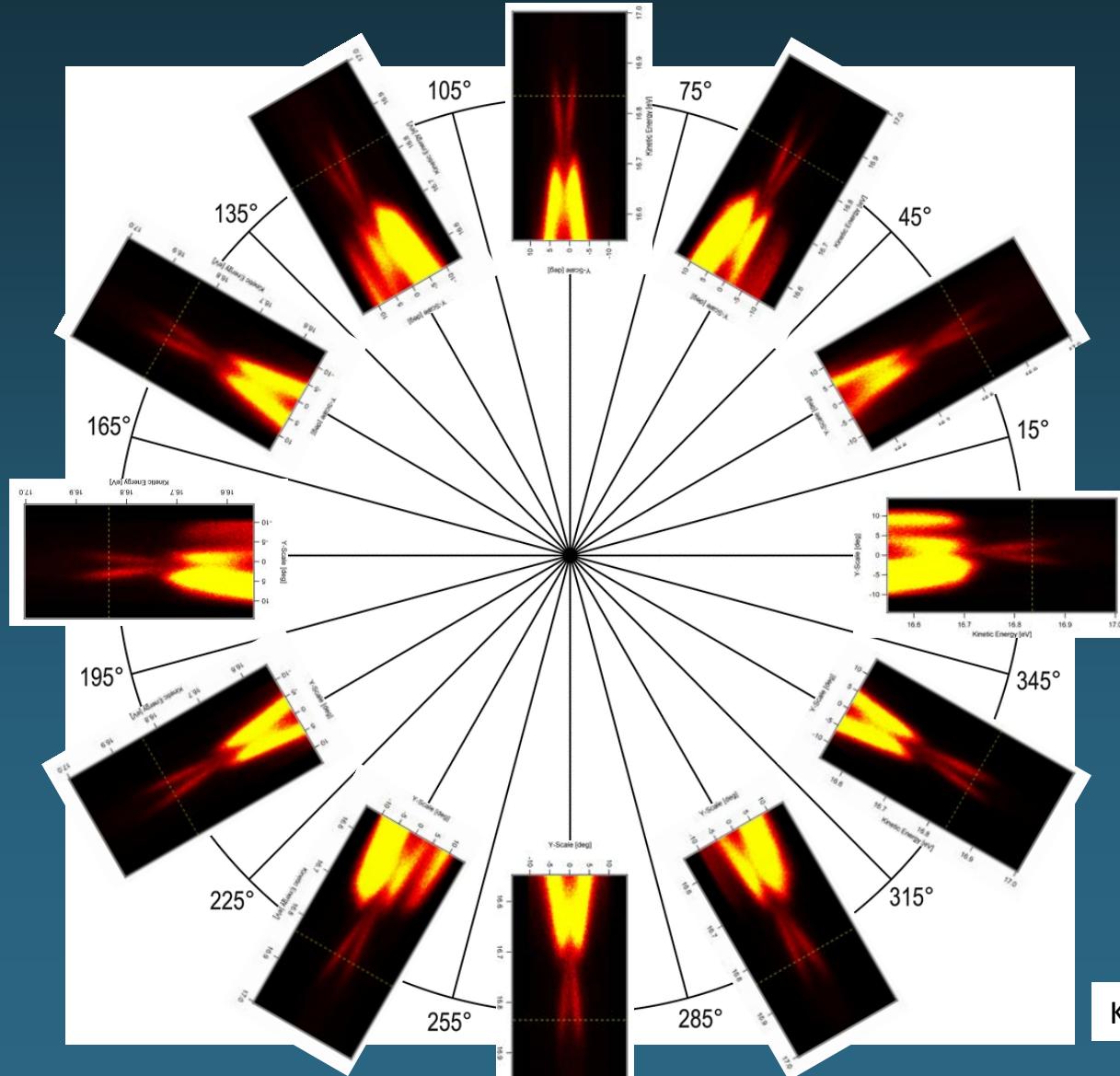
KH#63 (BaF<sub>2</sub>) ARPES @ RT    25 QL



surface = metallic  
bulk = insulator

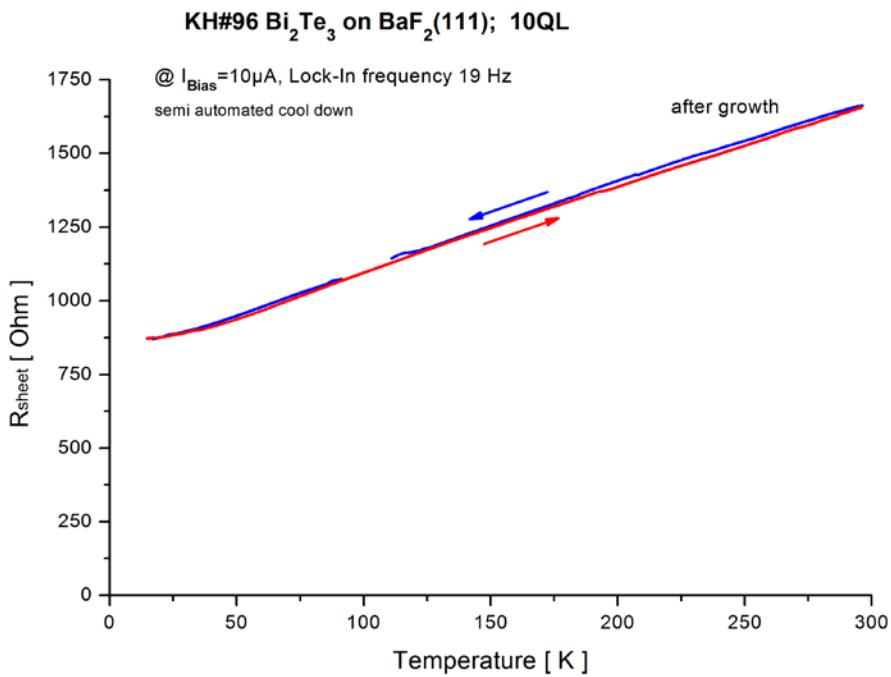
topological surface states  
not surface band bending

# ARPES : 3-fold symmetry



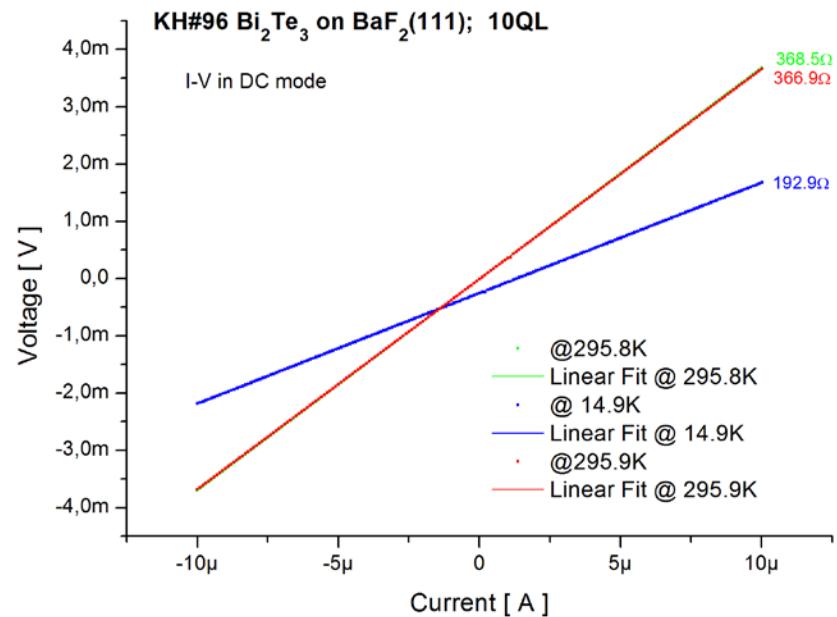
KH#81 (BaF<sub>2</sub>) 11QL

# *in-situ* electrical resistivity



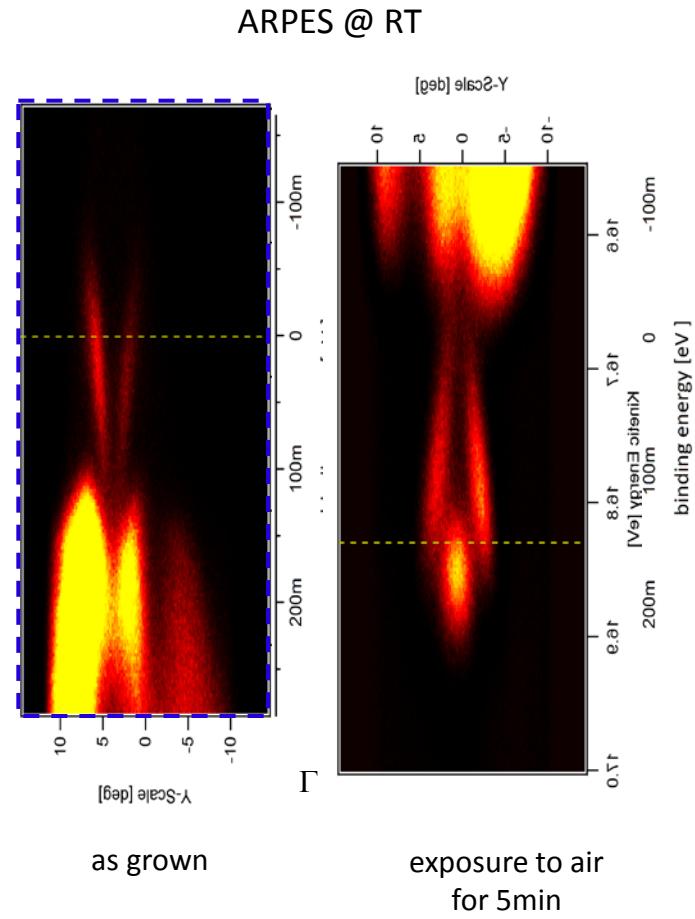
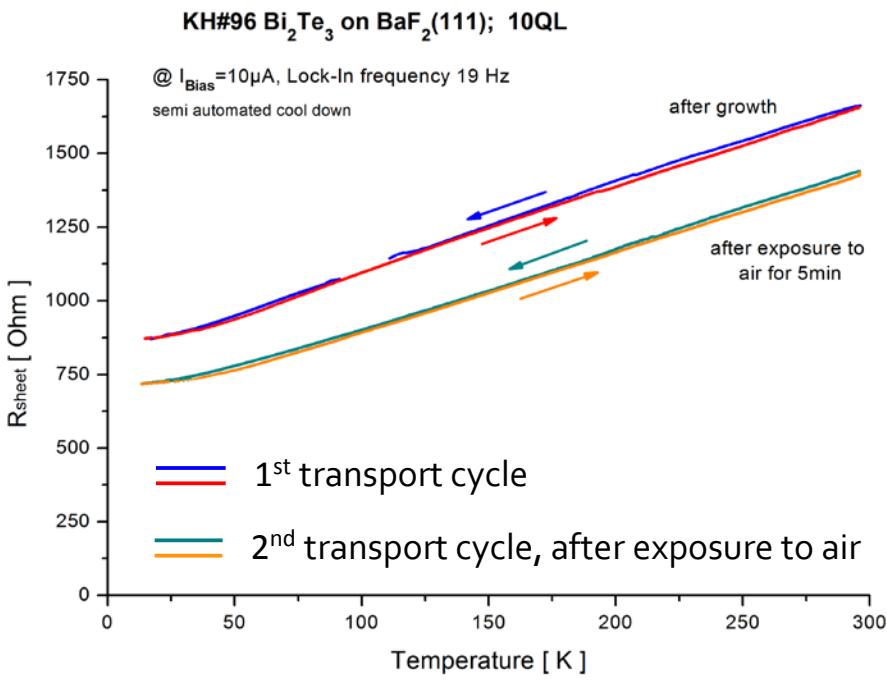
metallic- like behaviour

# *in-situ* electrical resistivity



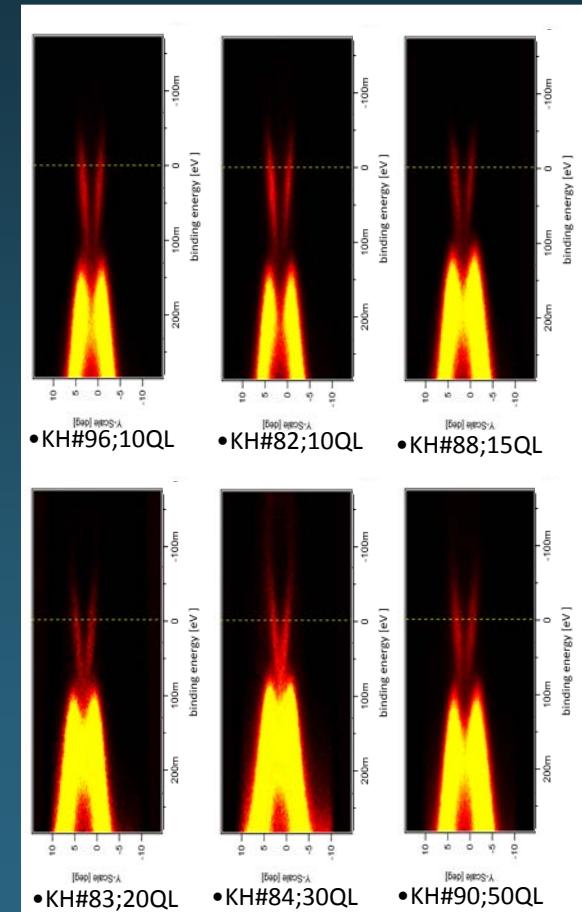
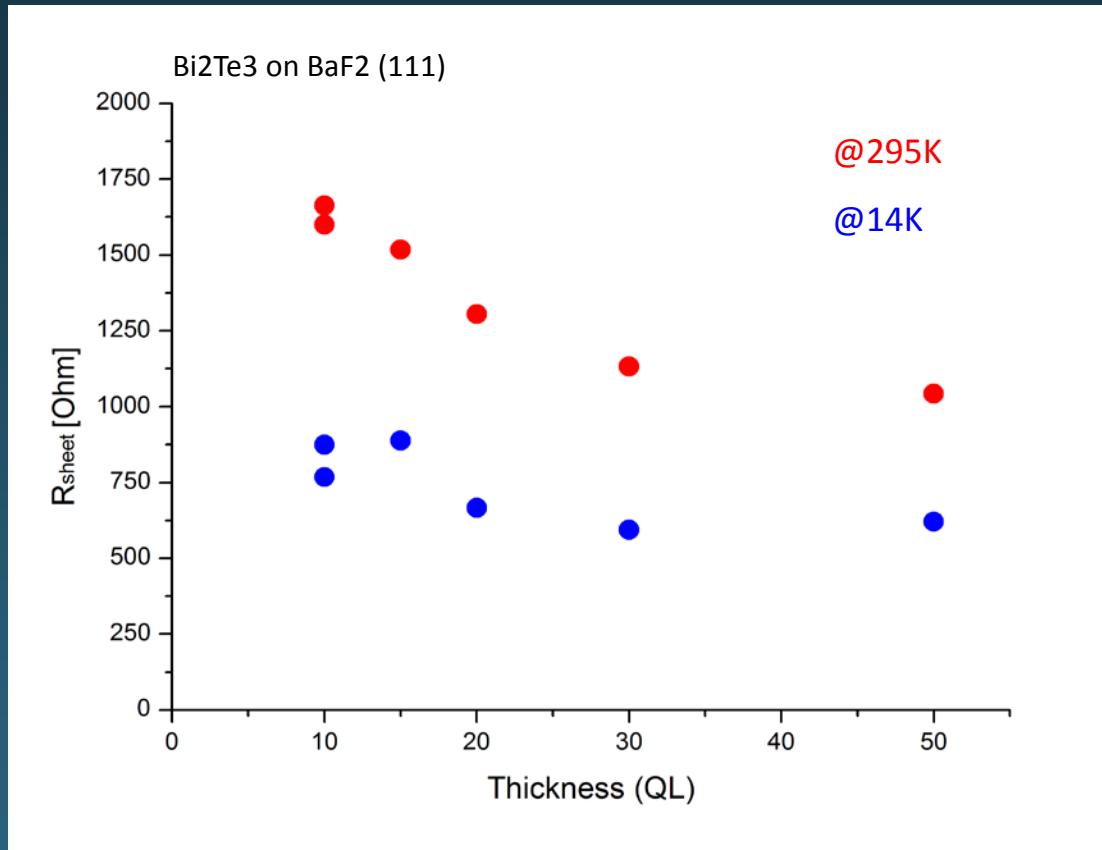
ohmic contacts

# electrical resistivity : contaminations



KH#96 (BaF2) 10QL

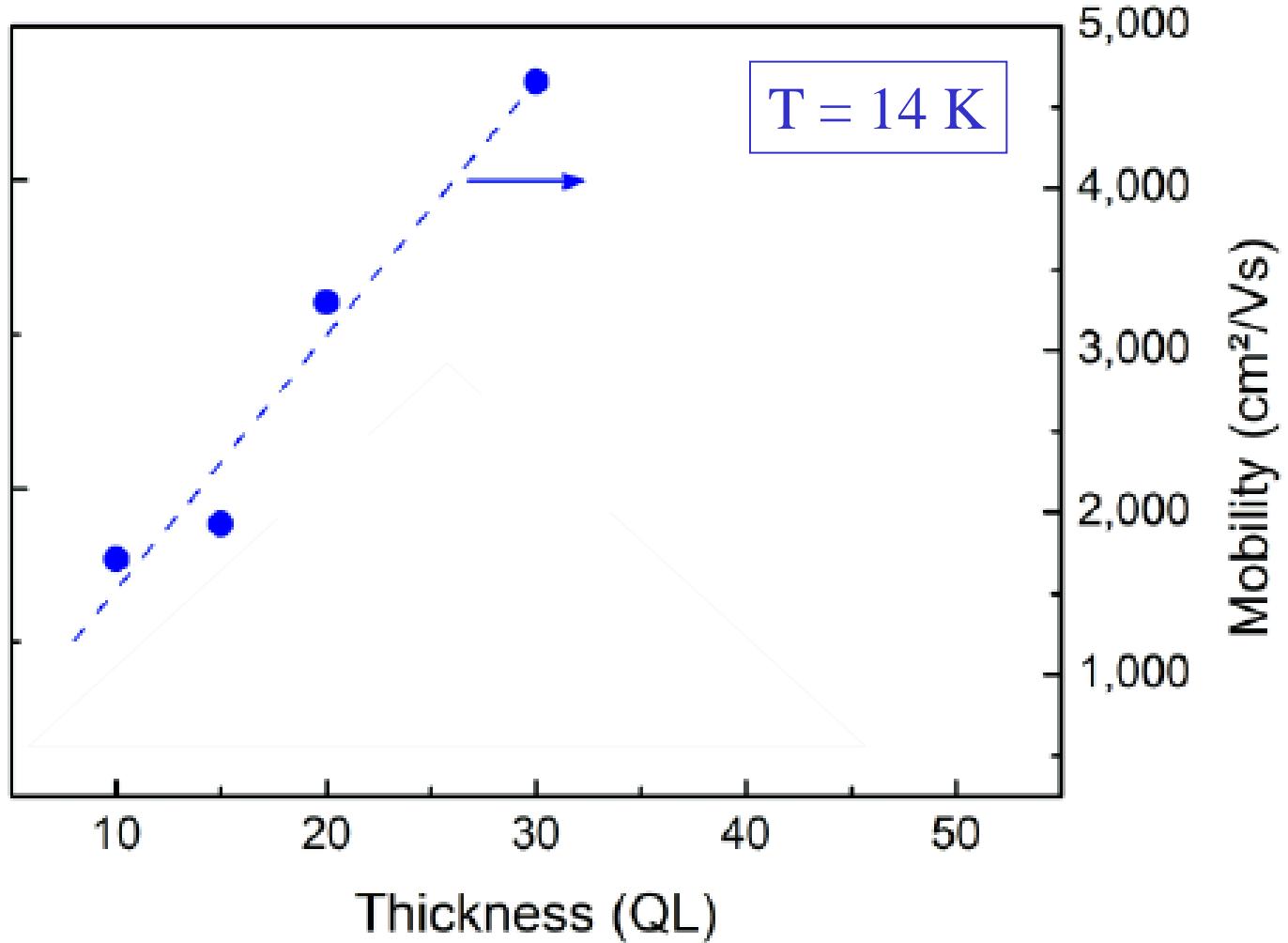
# *in-situ* electrical resistivity: thickness dependence



variation in resistivity by factor 1.6, while varying thickness by factor 5

⇒ Resistivity dominated by surface

very high mobilities



# Conclusions

- good epitaxial films of  $\text{Bi}_2\text{Te}_3$
- ARPES: films are insulating in the bulk, metallic at the surface
- in-situ resistivity:
  - good ohmic contacts
  - metallic behaviour > dominated by surface states
- resistivity and chemical potential extremely sensitive to adsorption of contaminants, especially water



PNAS 2014

## Intrinsic conduction through topological surface states of insulating $\text{Bi}_2\text{Te}_3$ epitaxial thin films

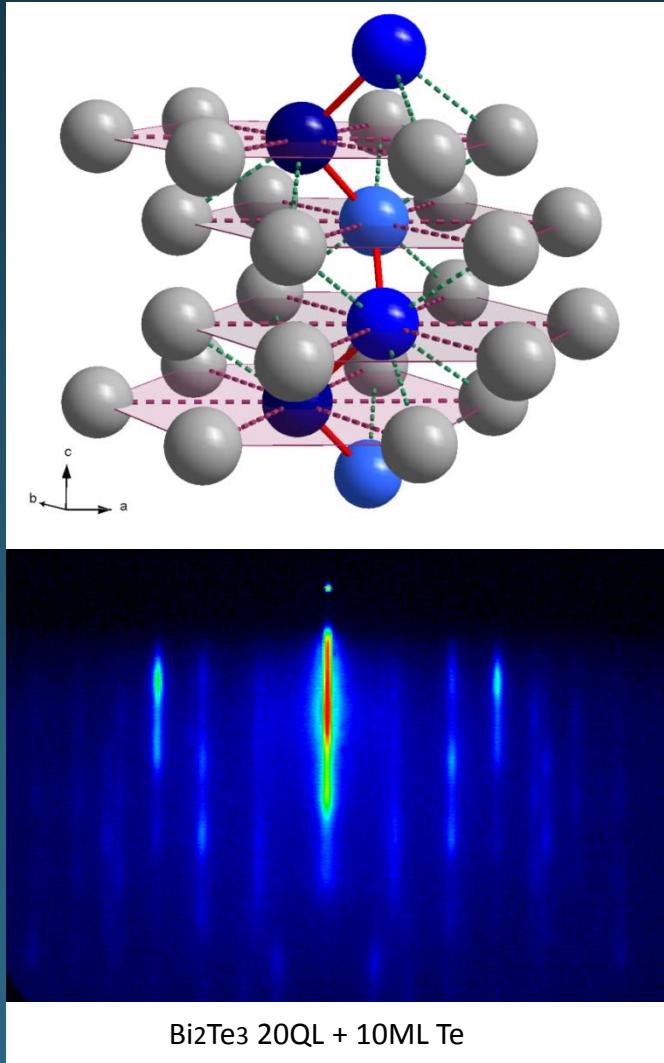
Katharina Hoefer<sup>a,1</sup>, Christoph Becker<sup>a</sup>, Diana Rata<sup>a</sup>, Jesse Swanson<sup>a,b</sup>, Peter Thalmeier<sup>a</sup>, and L. H. Tjeng<sup>a</sup>

<sup>a</sup>Max Planck Institute for Chemical Physics of Solids, Dresden 01187, Germany; and <sup>b</sup>University of British Columbia, Vancouver, BC, Canada V6T 1Z4

Edited by Zachary Fisk, University of California, Irvine, CA, and approved September 18, 2014 (received for review June 6, 2014)

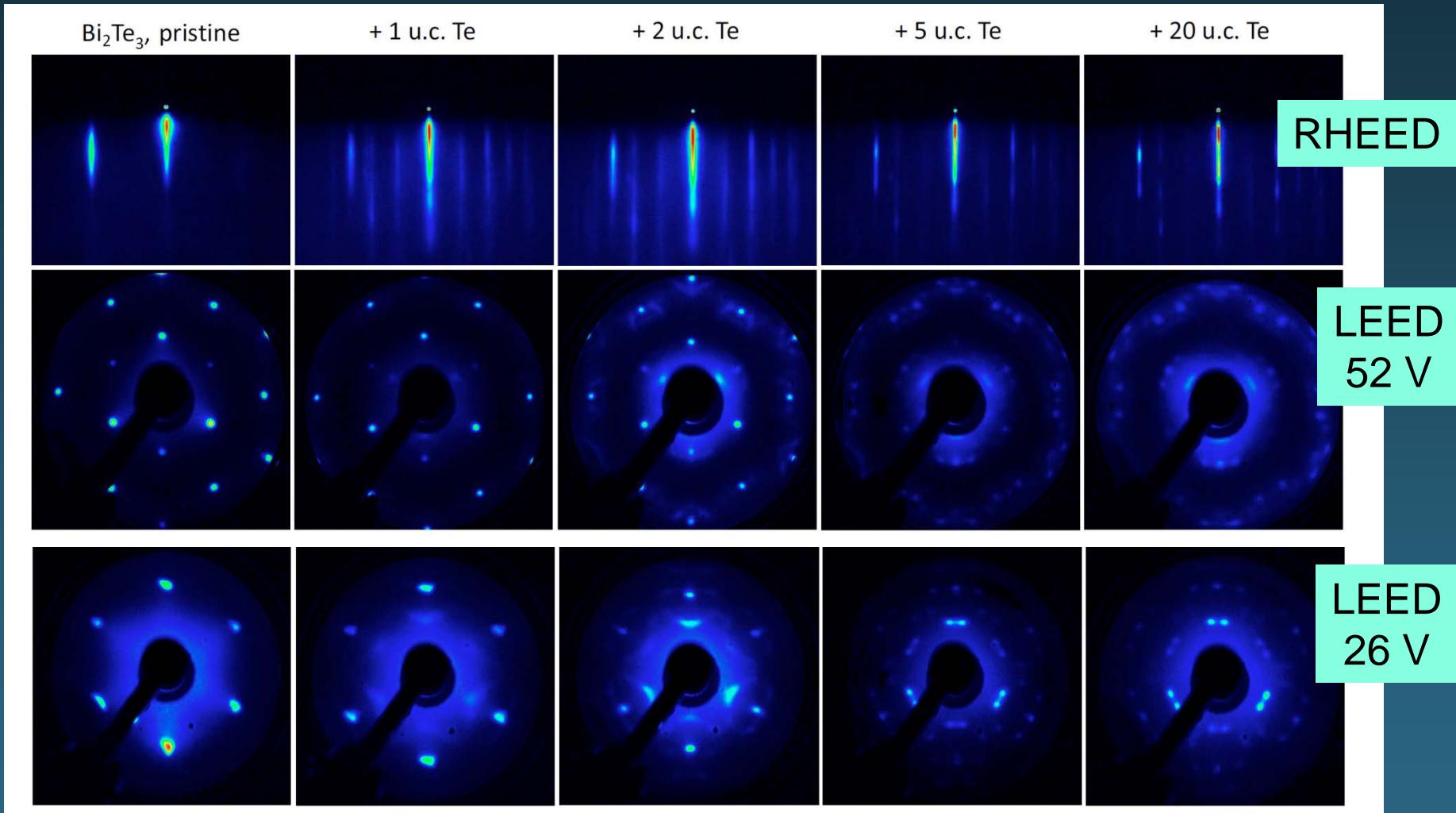
# Protective capping of topological surface states of Bi<sub>2</sub>Te<sub>3</sub>

## Capping with Tellurium



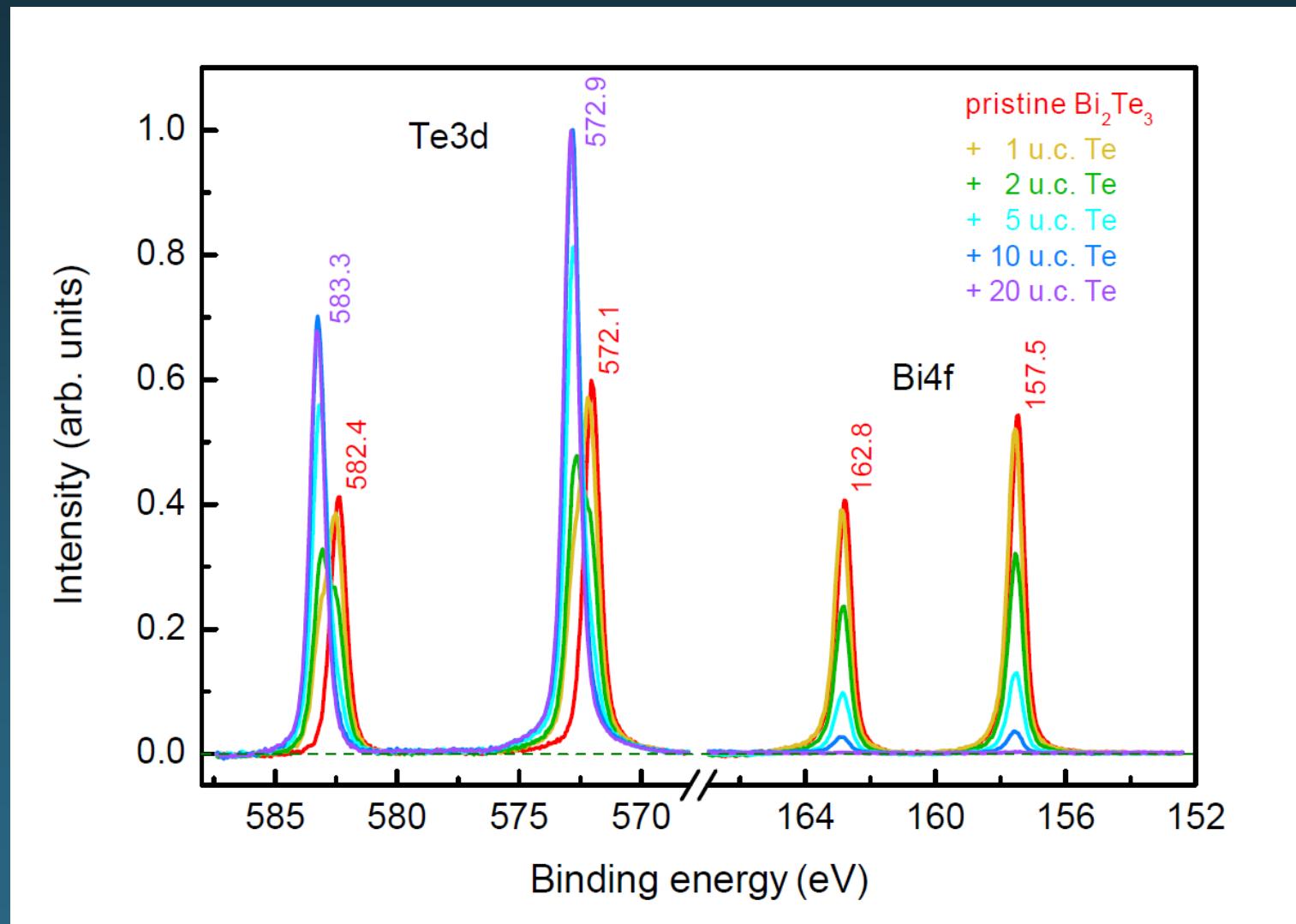
- trigonal crystal structure
  - $a = 4.456\text{\AA}$
  - $c = 5.927\text{\AA}$  ( $\triangleq 1\text{ML}$ )
- 1.6% mismatch to Bi<sub>2</sub>Te<sub>3</sub>
- half metal
  - $\rho_{\text{Te}} = 5 \text{ m}\Omega\text{m}$  ( $\parallel$  to c axis @ 20°C)
  - $\rho_{\text{Te}} = 1.5 \text{ m}\Omega\text{m}$  ( $\perp$  to c axis @ 20°C)
  - e.g. 10ML Te  $\Rightarrow R_{\square}(@\text{RT}) = 250 \text{ k}\Omega$
- Te is top layer of Bi<sub>2</sub>Te<sub>3</sub>
- MBE growth:
  - $T_{\text{Te}} = 185^\circ\text{C}$  (1 Å/min)
  - epitaxial growth on Bi<sub>2</sub>Te<sub>3</sub> @ RT
  - multi-domain

# Capping with Tellurium



epitaxial growth -- domains due 1.6% misfit

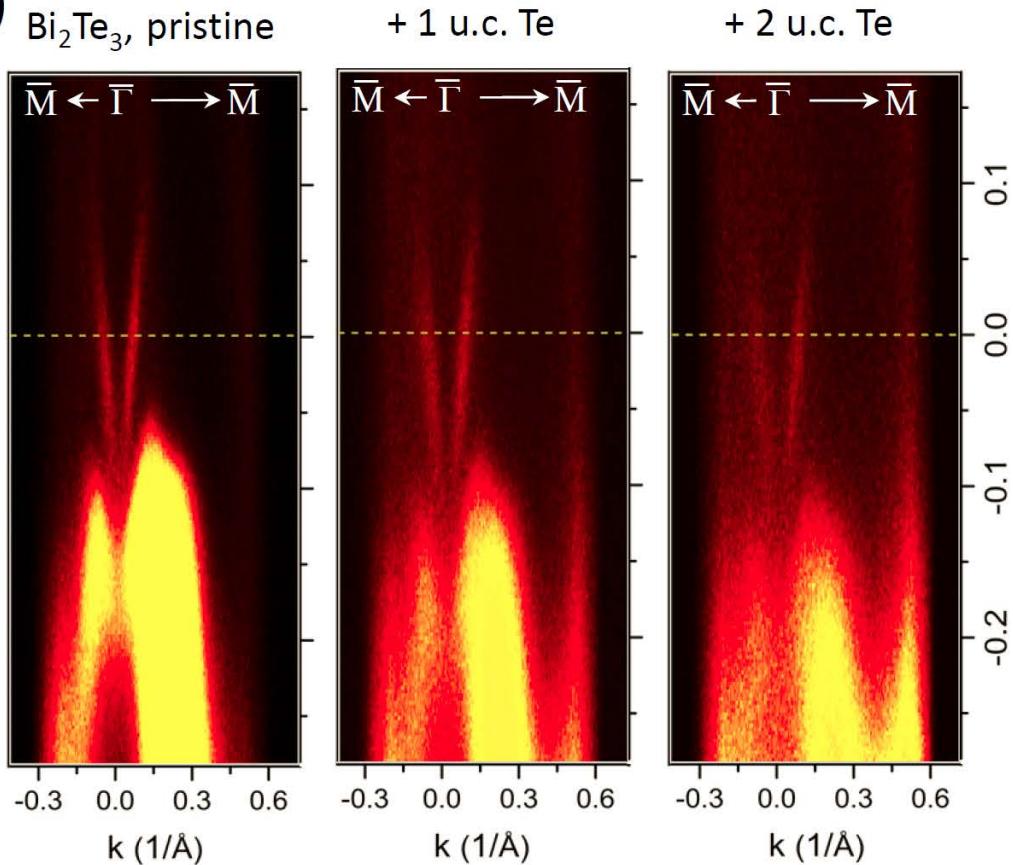
# Capping with Tellurium



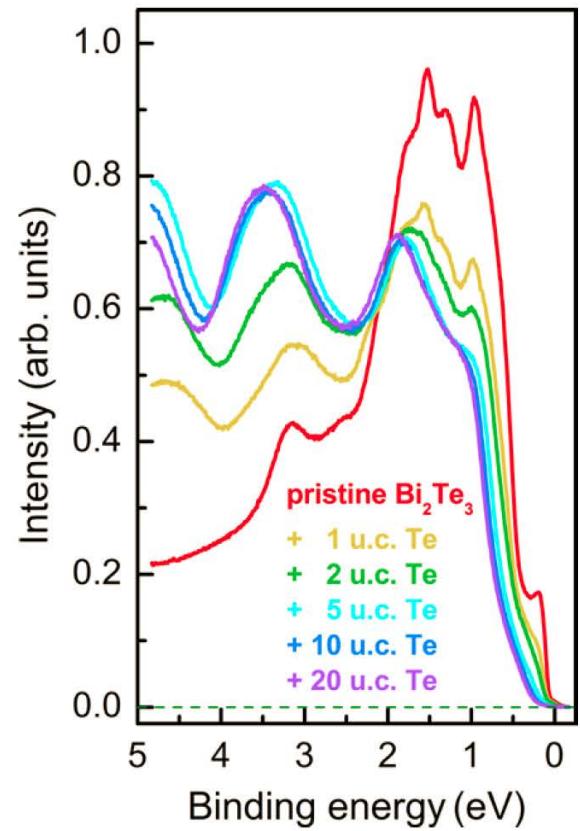
capping films are closed (no pinholes)

# Capping with Tellurium

(a)

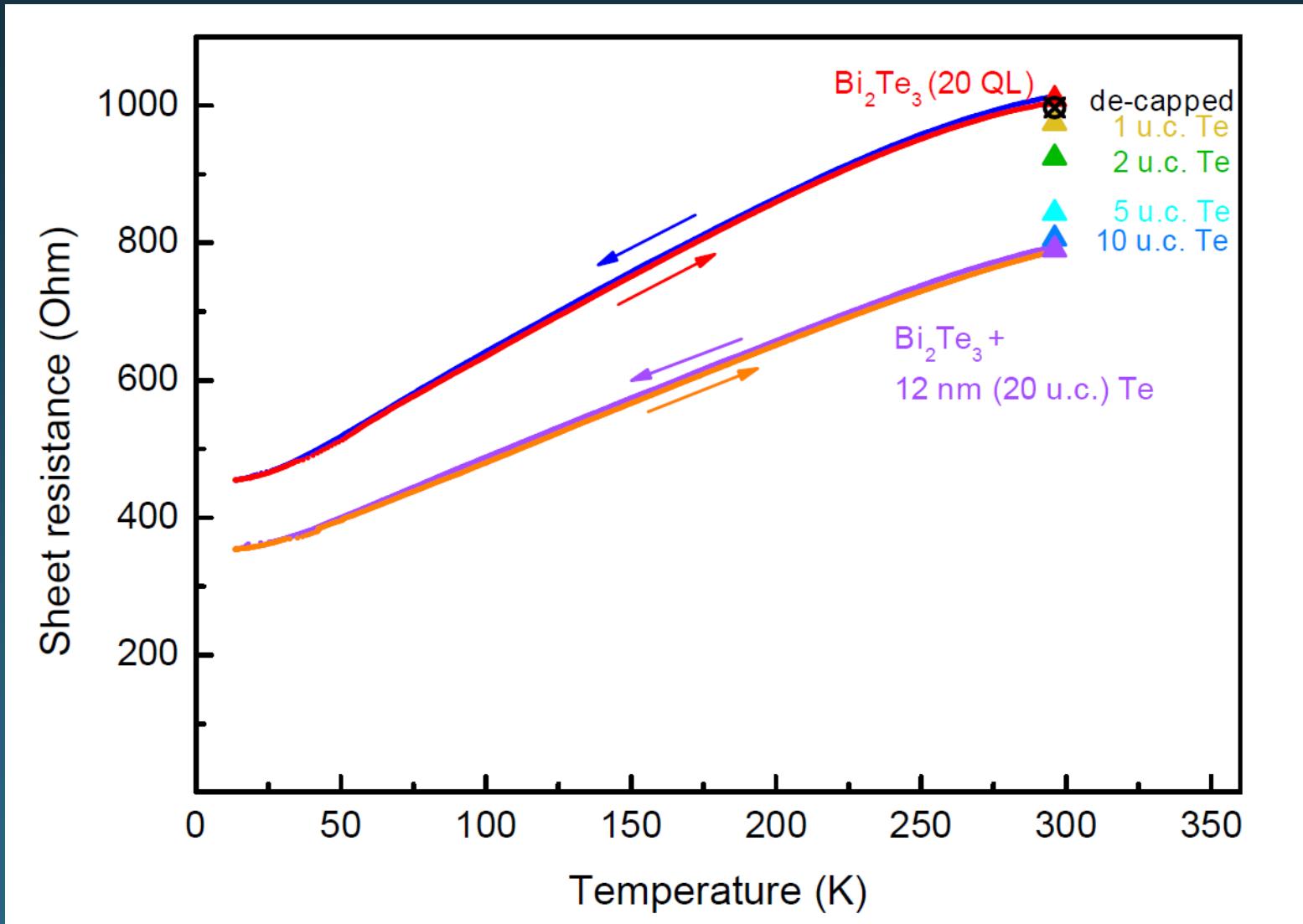


(b)



Te capping leaves surface states bands intact + no doping !

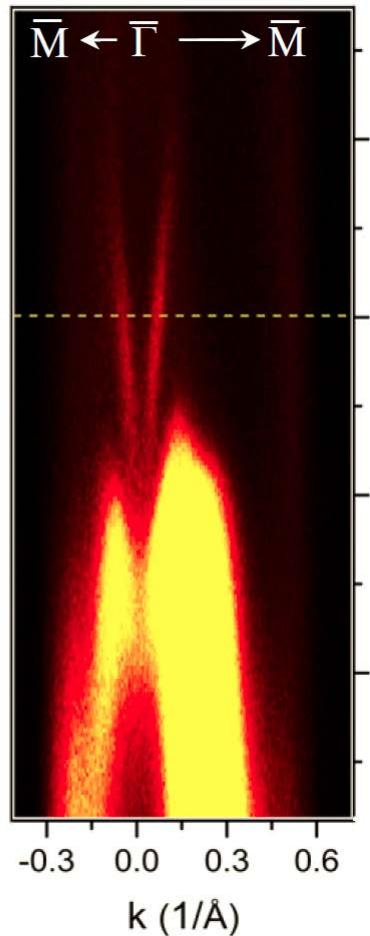
# Capping with Tellurium



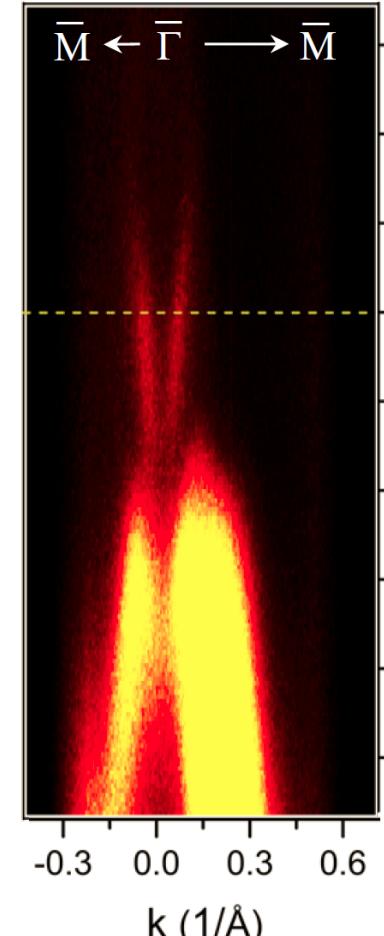
Te capping gives only small parallel conductivity

# Removing Tellurium capping

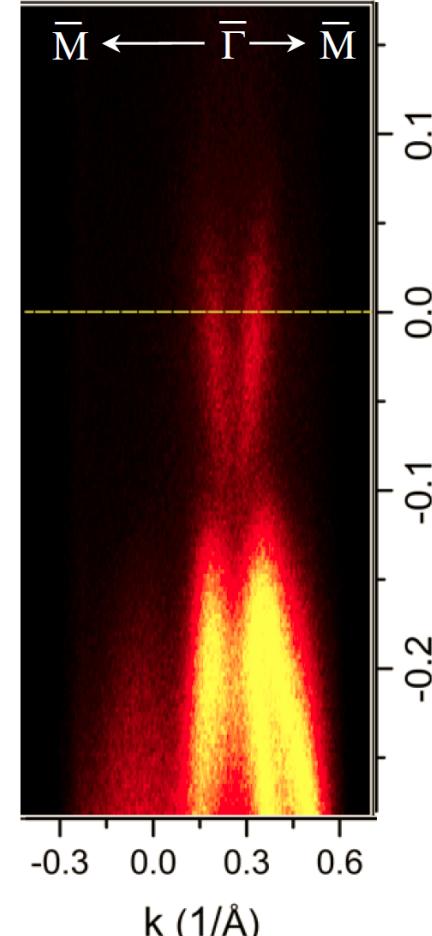
(a)  $\text{Bi}_2\text{Te}_3$ , pristine



(a) 20 u.c. Te removed



(b) 20 u.c. Te removed after 5 min air



Binding energy (eV)

Pristine state can be restored, also after air-exposure !

# capping of $\text{Bi}_2\text{Te}_3$ films with Te

- Capping by Te leaves the topological surface states intact (ARPES)
- No doping (ARPES), minor influence on conductivity (4 point)
- Epitaxy can be achieved (RHEED, LEED), no pinholes (XPS)
- Protective against air
- Capping can be removed, pristine state recovered (ARPES, 4 point)



AIP ADVANCES 5, 097139 (2015)



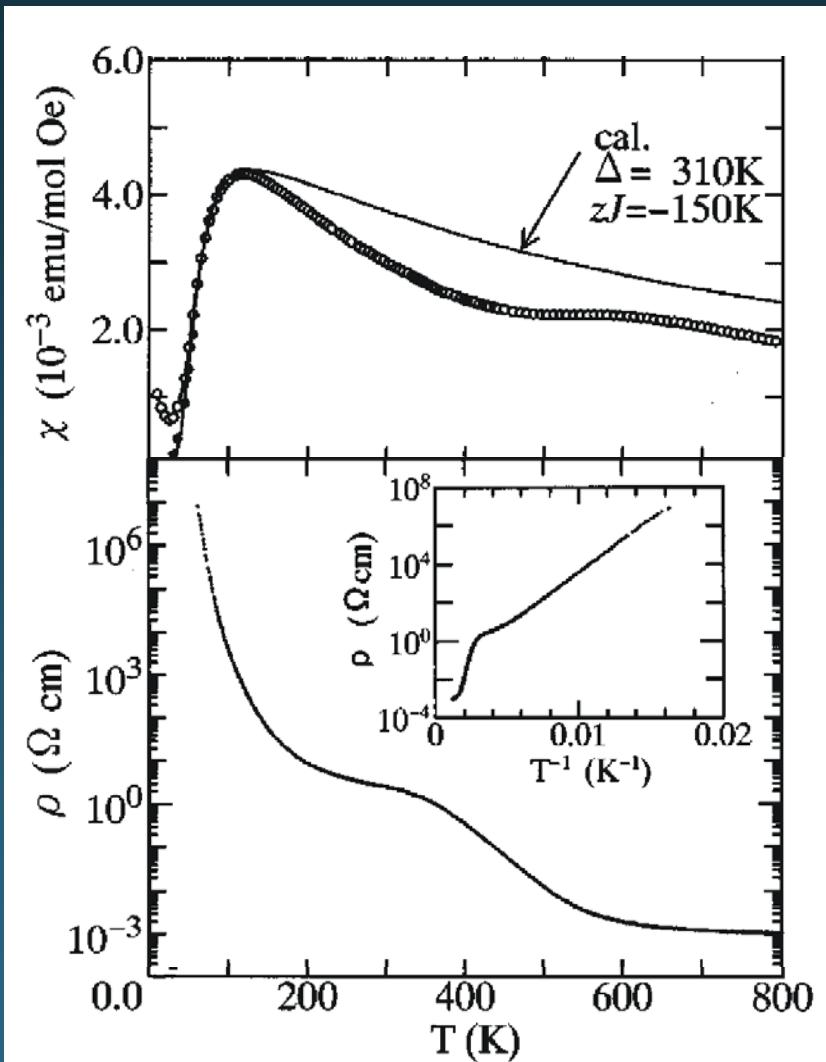
## Protective capping of topological surface states of intrinsically insulating $\text{Bi}_2\text{Te}_3$

Katharina Hoefer,<sup>a</sup> Christoph Becker, Steffen Wirth, and Liu Hao Tjeng<sup>b</sup>  
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Dresden 01187, Germany*

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# $\text{LaCoO}_3$ : a benchmark system

$\text{Co}^{3+}$ :  $3d^6$

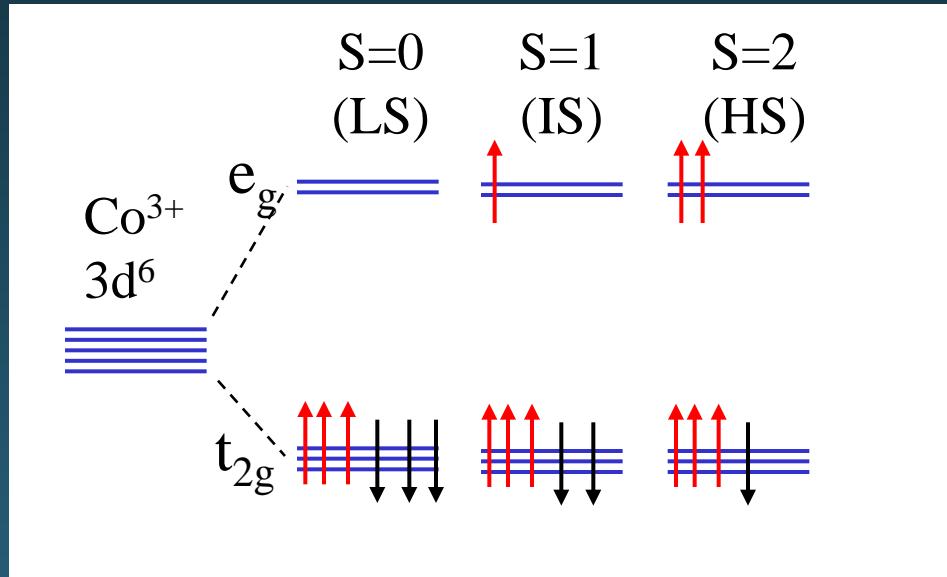


S. Yamaguchi *et al.*, PRB **53**, 2926 (1996)

- non-magnetic insulator at low T
- non-magnetic to paramagnetic transition for  $T > 25\text{K}$ , with max. in magn. susceptibility at  $100\text{K}$
- resistivity drop  $T = 350\text{K} - 550\text{K}$ , “metal-insulator transition”

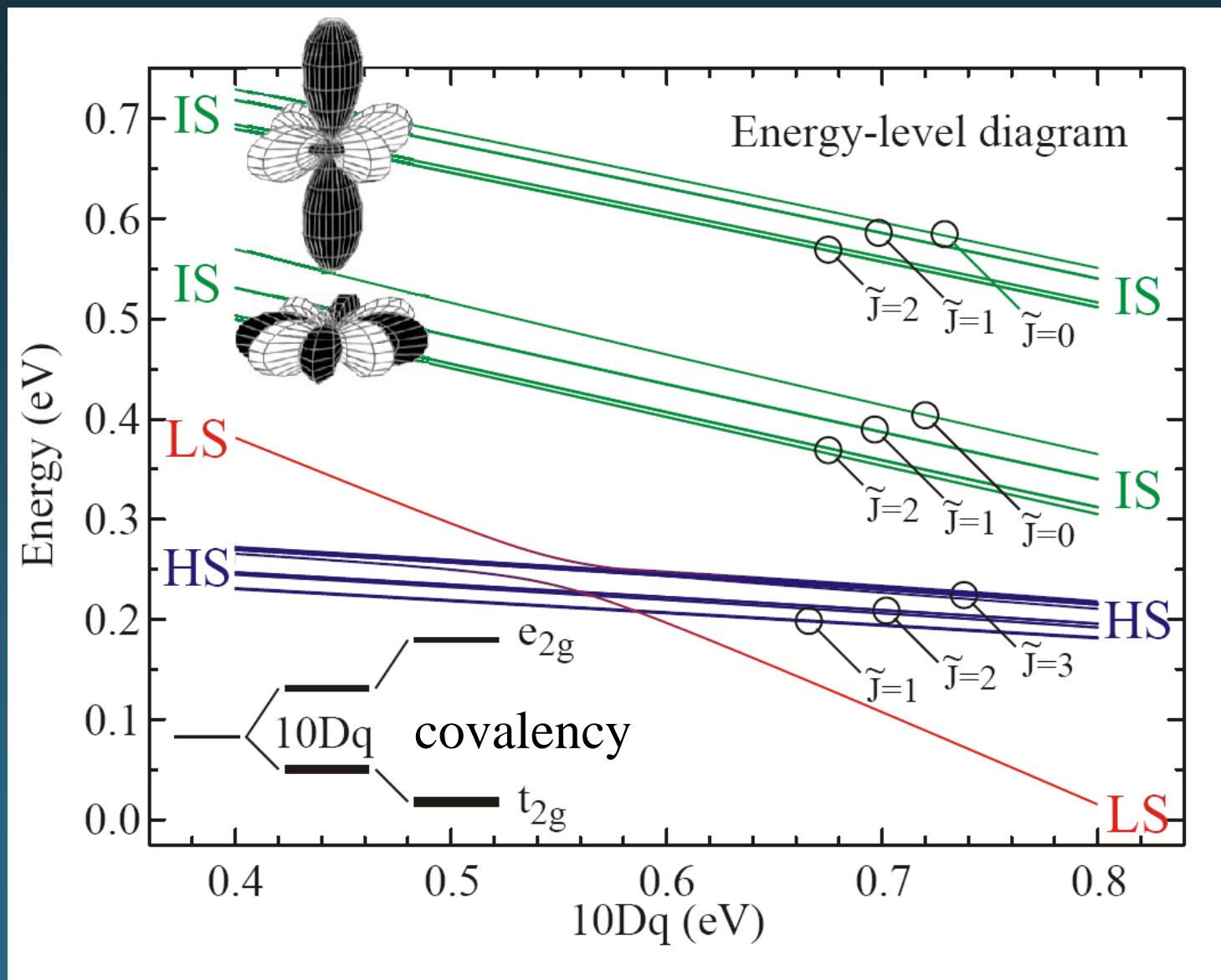
Spin-state transitions ?  
Low – Intermediate – High spin ?

# Puzzle: what is the spin state of $\text{Co}^{3+}$ ??

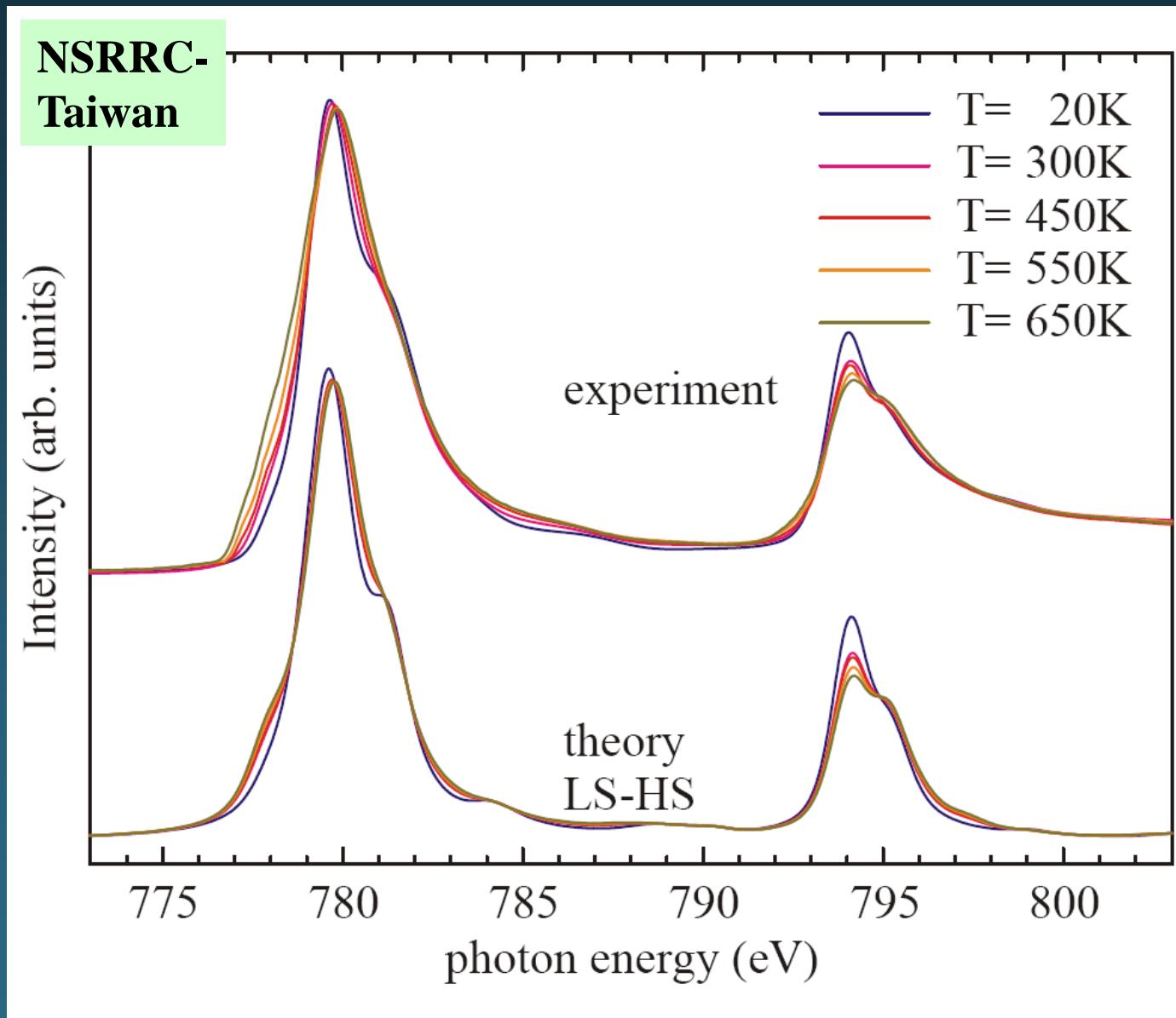


competition:  
crystal field - band formation - Hund's exchange

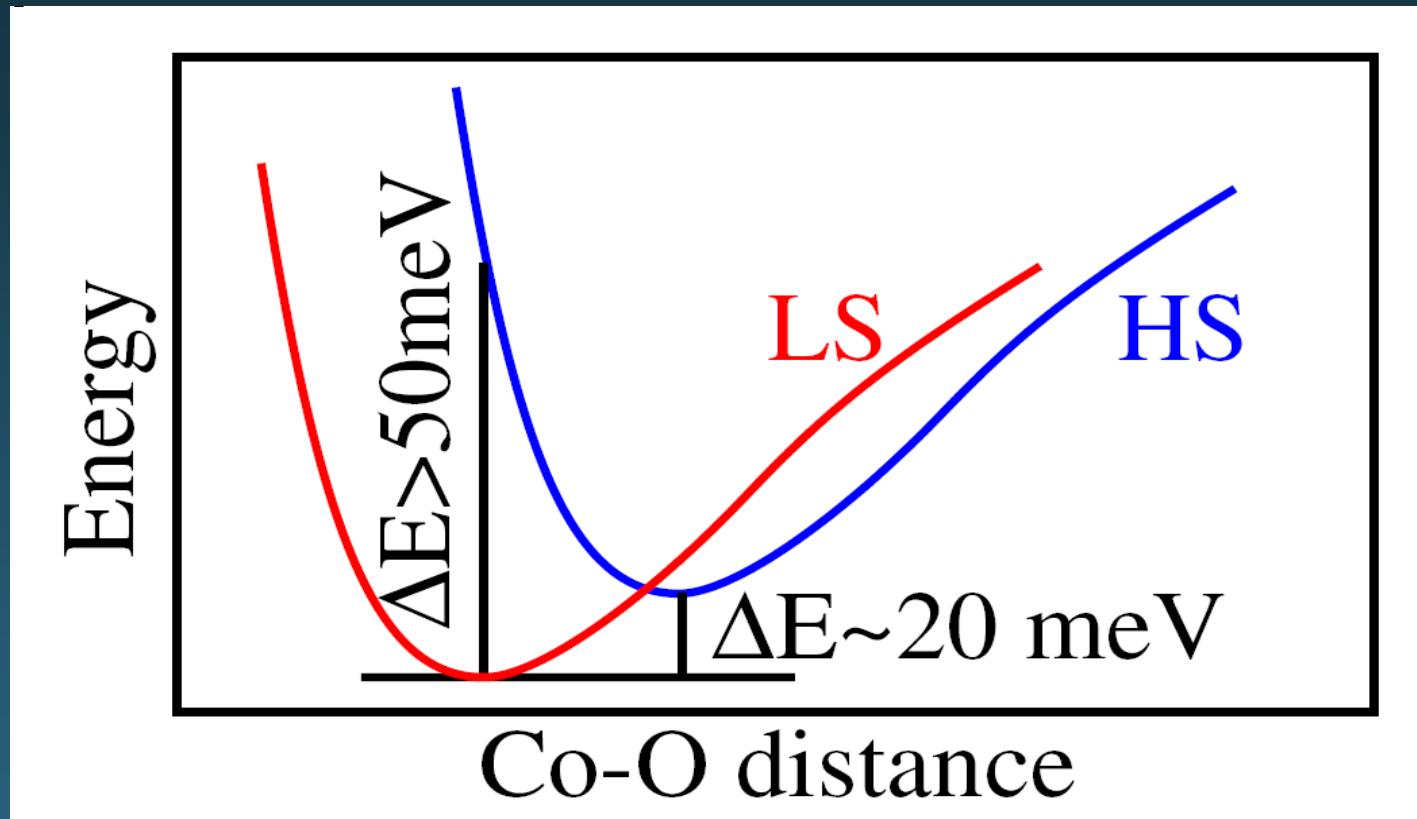
# Energy level diagram: $\text{CoO}_6$ cluster incl. covalency



# XAS study on the spin state of $\text{Co}^{3+}$ ion in $\text{LaCoO}_3$

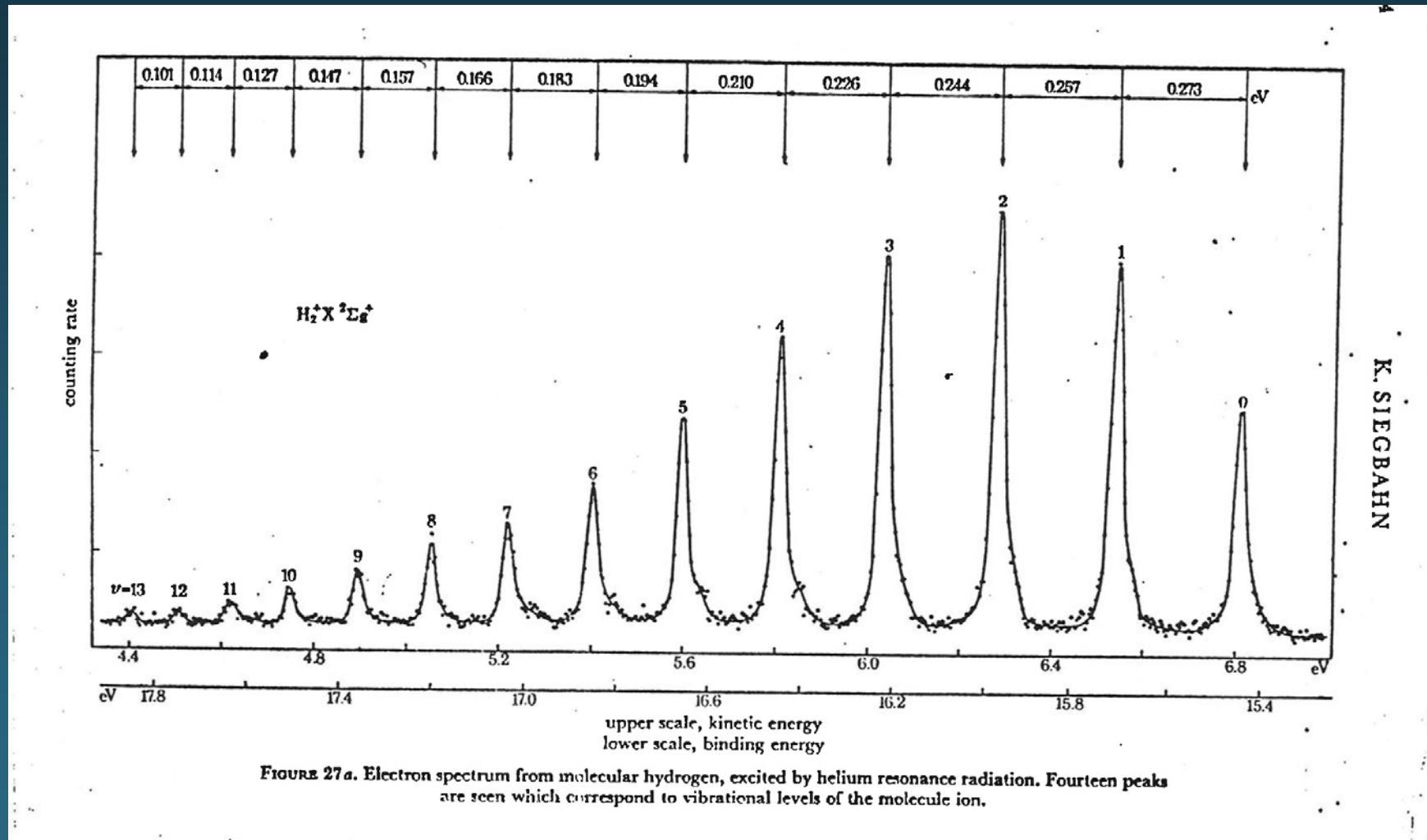


# Spin state transition: local lattice relaxation



- frozen lattice:  $\Delta E \gg k_B T$   
*otherwise too much Van Vleck and incorrect XAS spectra*
- inhomogeneous mixed spin-state system

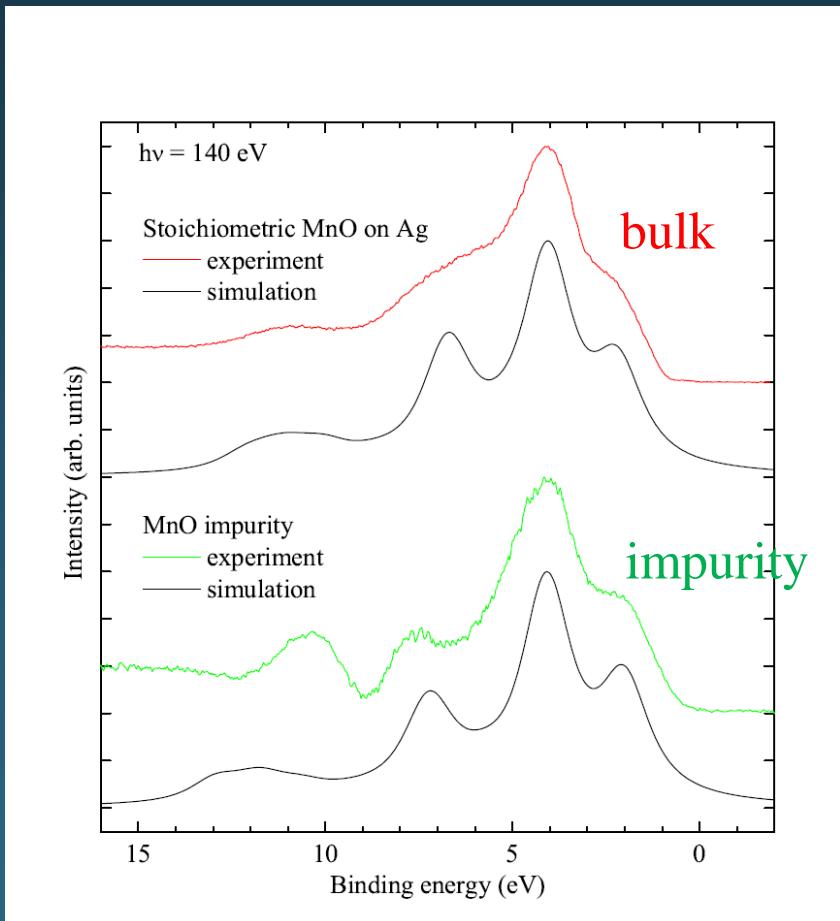
## H<sub>2</sub>-molecule: photoemission and vibrational levels



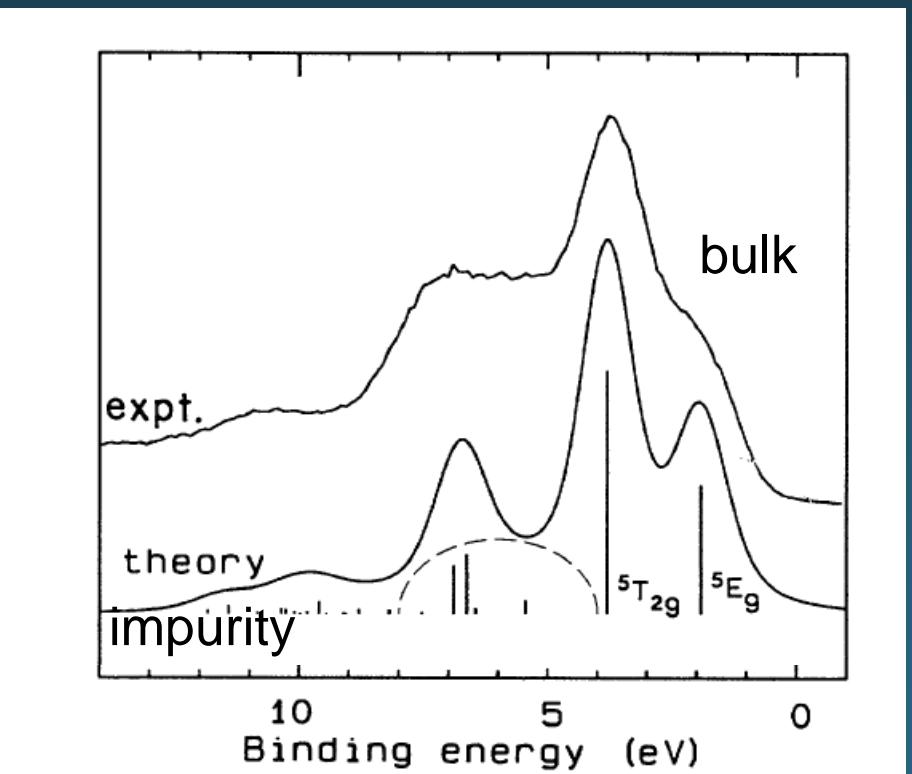
# MnO bulk vs Mn in MgO

# propagation of an extra hole in MnO

Haupricht thesis 2010

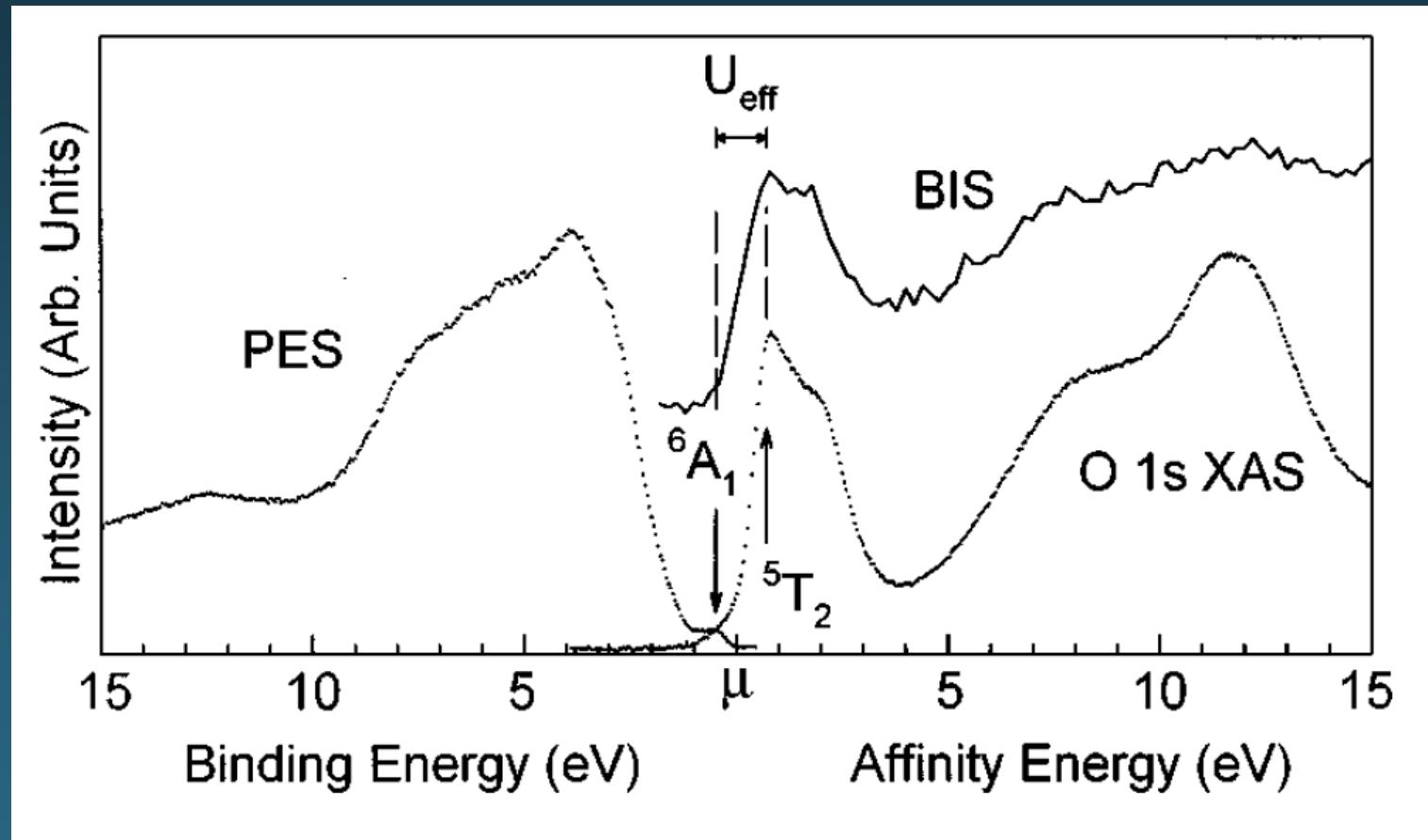


van Elp et al. PRB 1991



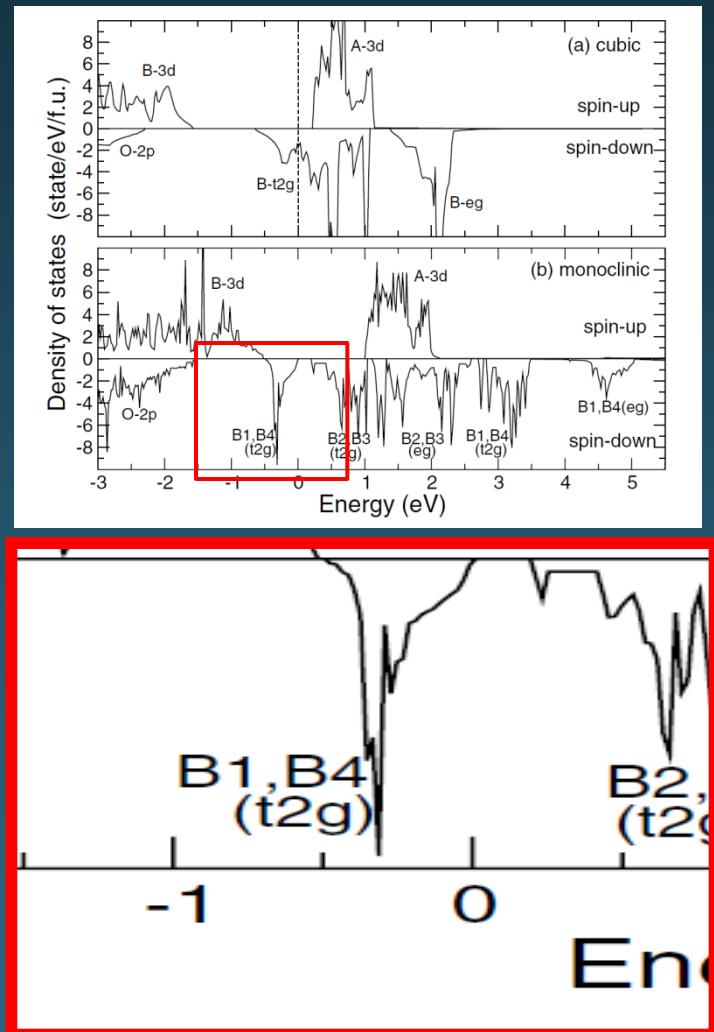
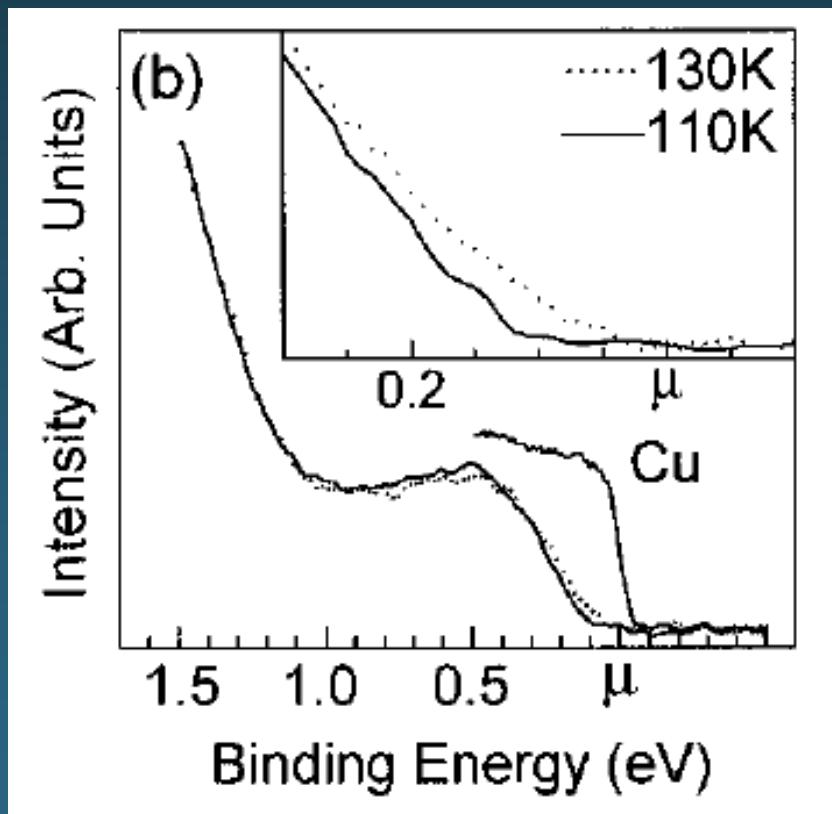
# $\text{Fe}_3\text{O}_4$ : an insulator at low temperatures

Park, Tjeng, Allen et al. PRB 1997



# $\text{Fe}_3\text{O}_4$ : an insulator at low temperatures

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# **Fe<sub>3</sub>O<sub>4</sub>: Polarons and Verwey transition ?**

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## **High-energy photoemission on Fe<sub>3</sub>O<sub>4</sub>: Small polaron physics and the Verwey transition**

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## **Polaronic Behavior of Photoelectron Spectra of Fe<sub>3</sub>O<sub>4</sub> Revealed by Both Hard X-ray and Extremely Low Energy Photons**

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## Modification of material properties using image charge screening

Reduction of charge excitation energies:

- Coulomb energy:  $U = U_o - 2E_{\text{image}}$
- Charge transfer energy:  $\Delta = \Delta_o - 2E_{\text{image}}$
- Bandgap:  $E_g = E_{go} - 2E_{\text{image}}$

Examples from experiments:

- Monolayer C<sub>60</sub> on Ag : U and E<sub>g</sub> reduced by 1 eV
- MgO film on Ag : U and Δ reduced by 2 eV
- NiO on Ag vs on MgO : influence on Neel temperature
- Te film on Bi<sub>2</sub>Te<sub>3</sub> : more conducting due to polarization ?

## Small polarons: energy lowering

- Spin state transition in LaCoO<sub>3</sub>
- Propagation of extra hole in MnO, Fe<sub>3</sub>O<sub>4</sub>